

Integration of Functional Oxides and Semiconductors:

Magnetism and Epitaxy

Alex Demkov

The University of Texas at Austin



Texas A&M University, Commerce, November 2013

People involved:



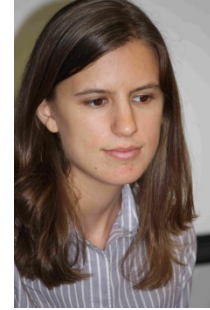
Hosung Seo



Miri Choi



Patrick Ponath



Kristy Kormondy



Agham Posadas



Chandrima Mitra



Chungwei Lin



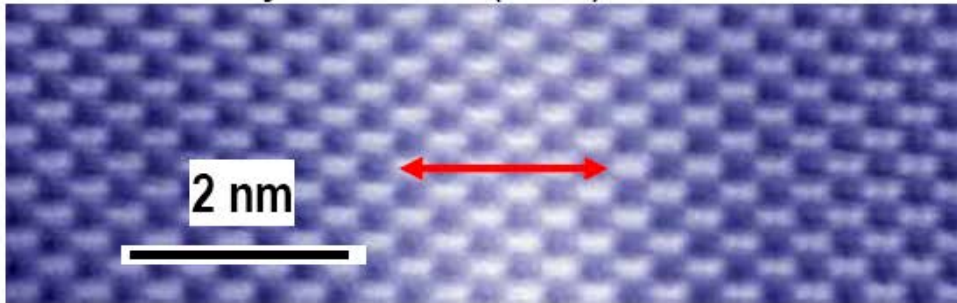
Richard Hatch

Outline of the talk

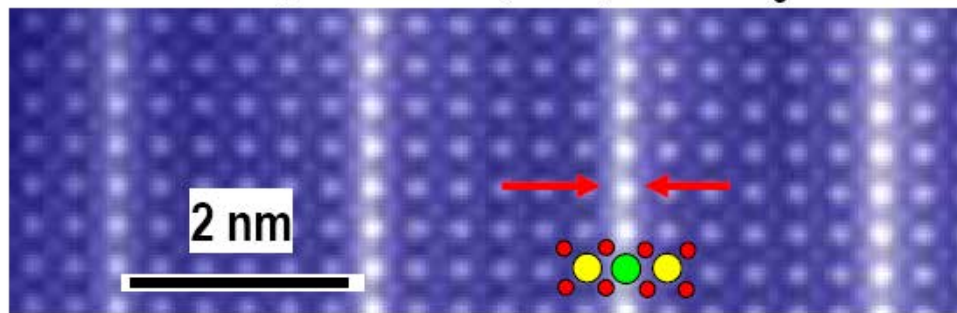
- **Introduction**
- **Magnetism in Oxides**
- **Molecular Beam Epitaxy**
- **COX**
- **LaCoO₃ on Si**
- **Conclusions**

Advances in Oxide Epitaxy

1 monolayer Sb in (100) Silicon



1 monolayer La in (100) SrTiO₃

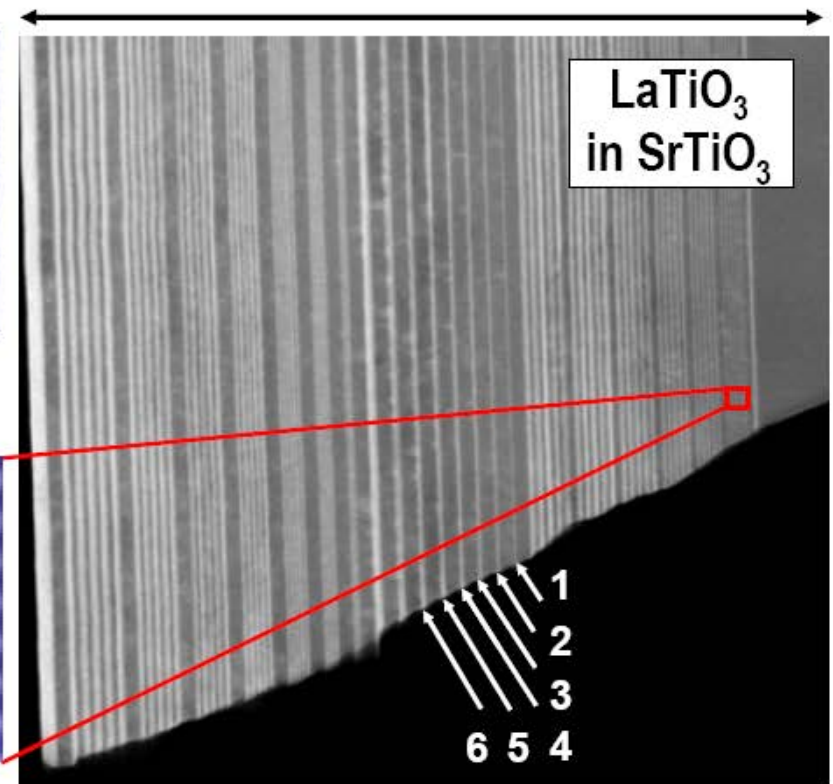


● La³⁺

● Sr²⁺

● Ti³⁺/Ti⁴⁺

500 nm



Superlattices by design

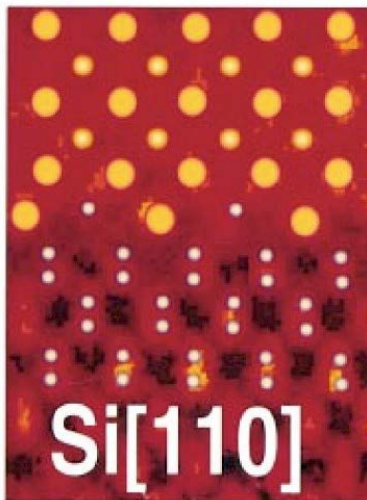
A. Ohtomo, D. A. Muller, J. A. Grazul, and H. Y. Hwang, *Nature* **419**, 378 (2002).

Epitaxial oxide on semiconductors

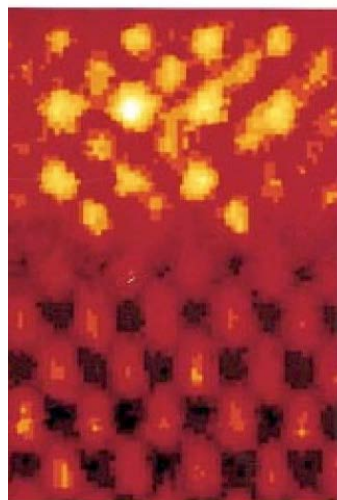


SrTiO₃ on Si

Model



Experiment



BaTiO₃ on Ge

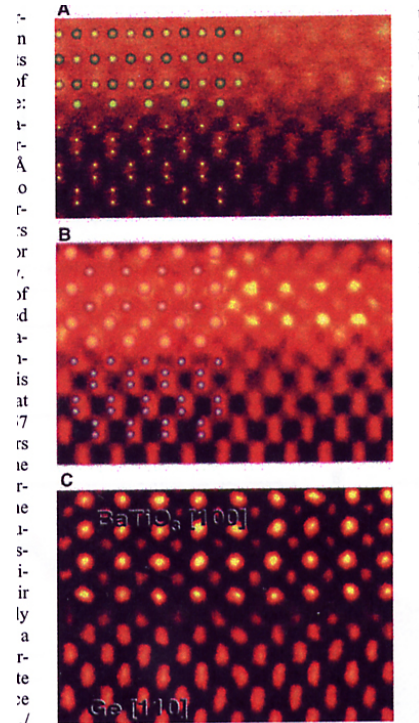
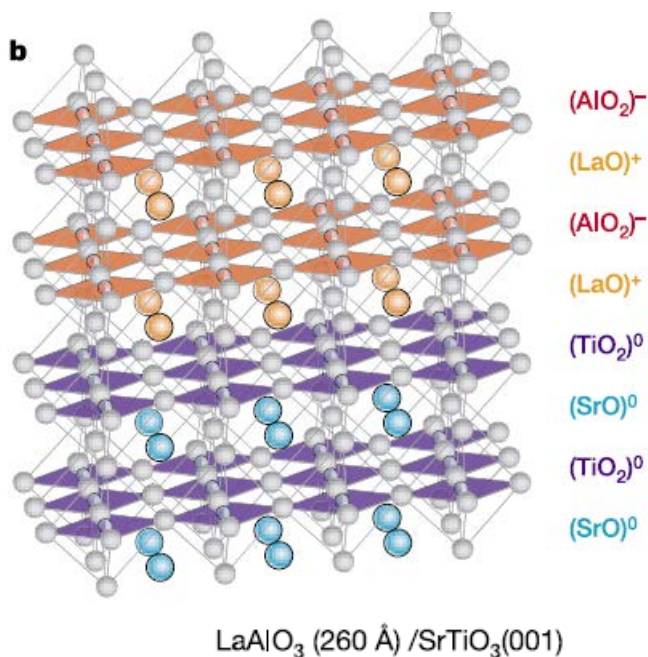


Fig. 1. Alkaline earth and perovskite oxide heteroepitaxy on silicon and germanium. The figure illustrates our ability to manipulate interface structure at the atomic level using our (AO)_n(A'BO₃)_m structure series. The *n/m* ratio defines the electrical characteristics of this new physical system of COS in a MOS capacitor. In (A), *n* = 3, *m* = 0; in (B), *n* = 1, *m* = 2; in (C), *n* = 0, *m* = 3.

R. McKee, F. Walker, M. Chisholm, *PRL* 81 3014 (1998)
 R. McKee, F. Walker, M. Chisholm, *Science* 293, 468 (2001)

SrTiO₃/LaAlO₃ heterostructure:

letters to nature



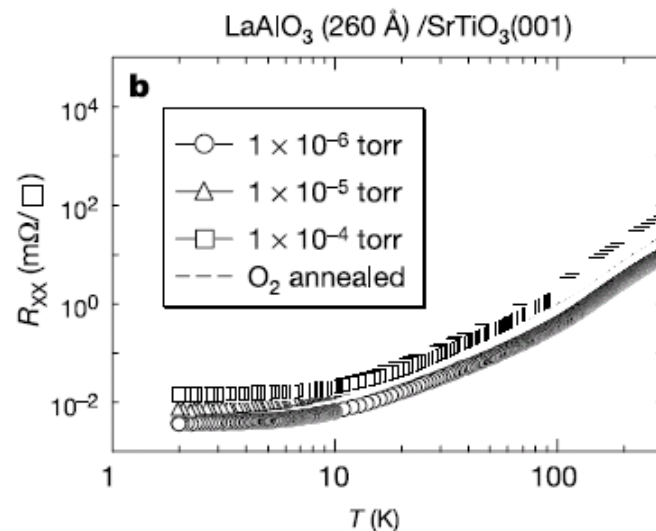
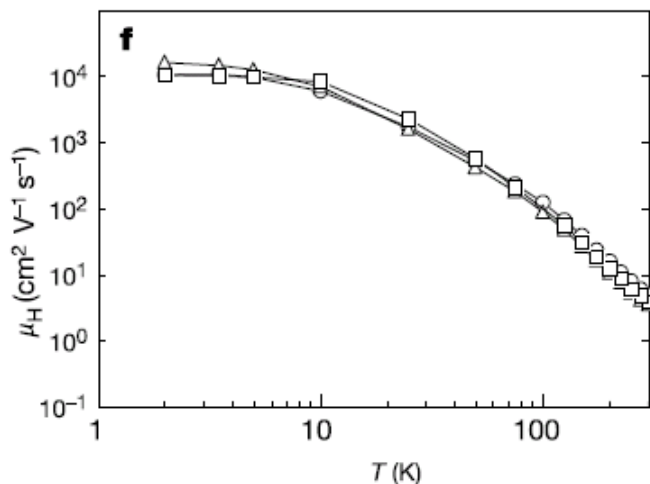
A high-mobility electron gas at the LaAlO₃/SrTiO₃ heterointerface

A. Ohtomo^{1,2,3} & H. Y. Hwang^{1,3,4}

¹Bell Laboratories, Lucent Technologies, Murray Hill, New Jersey 07974, USA
²Institute for Materials Research, Tohoku University, Sendai, 980-8577, Japan
³Japan Science and Technology Agency, Kawaguchi, 332-0012, Japan
⁴Department of Advanced Materials Science, University of Tokyo, Kashiwa, Chiba, 277-8651, Japan

limit, this interface presents an extra half electron or hole per two-dimensional unit cell, depending on the structure of the interface. The hole-doped interface is found to be insulating, whereas the electron-doped interface is conducting, with extremely high carrier mobility exceeding $10,000 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$. At low temperature, dramatic magnetoresistance oscillations periodic with the inverse magnetic field are observed, indicating quantum transport. These results present a broad opportunity to tailor low-dimensional charge states by atomically engineered oxide heteroepitaxy.

An early discussion of polarity or valence discontinuities arose in the consideration of the growth of GaAs on (001)-oriented Ge^{1,2}. Both semiconductors have the same crystal structure and nearly



ARTICLES

Why some interfaces cannot be sharp

NAOYUKI NAKAGAWA^{1,2}, HAROLD Y. HWANG^{1,2} AND DAVID A. MULLER^{3*}

¹Department of Advanced Materials Science, University of Tokyo, Kashiwa, Chiba 277-8561, Japan

²Japan Science and Technology Agency, Kawaguchi 332-0012, Japan

³School of Applied and Engineering Physics, Cornell University, Ithaca, New York 14853, USA

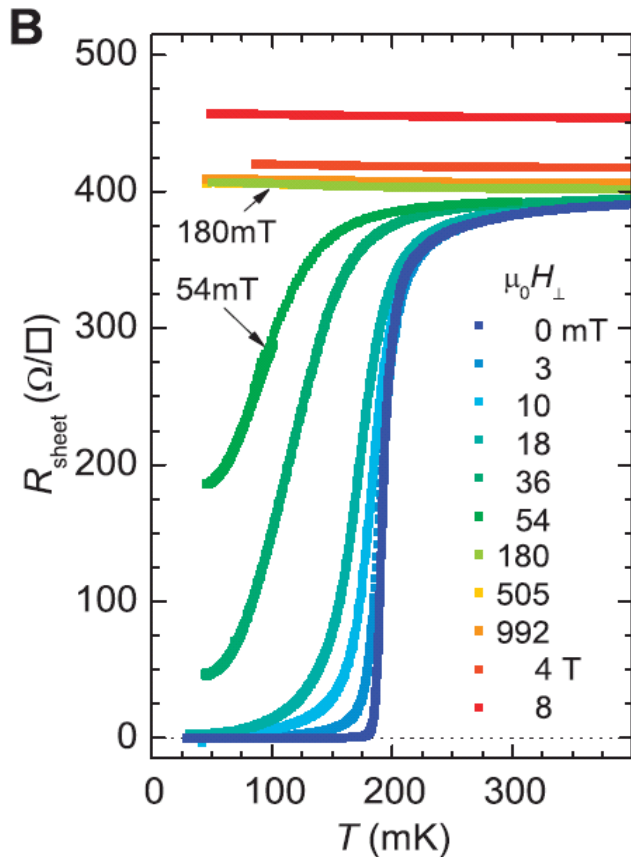
*e-mail: davidm@cornell.edu

H. W. Hwang *et al.*, *Nature* 427, 423 (2004)

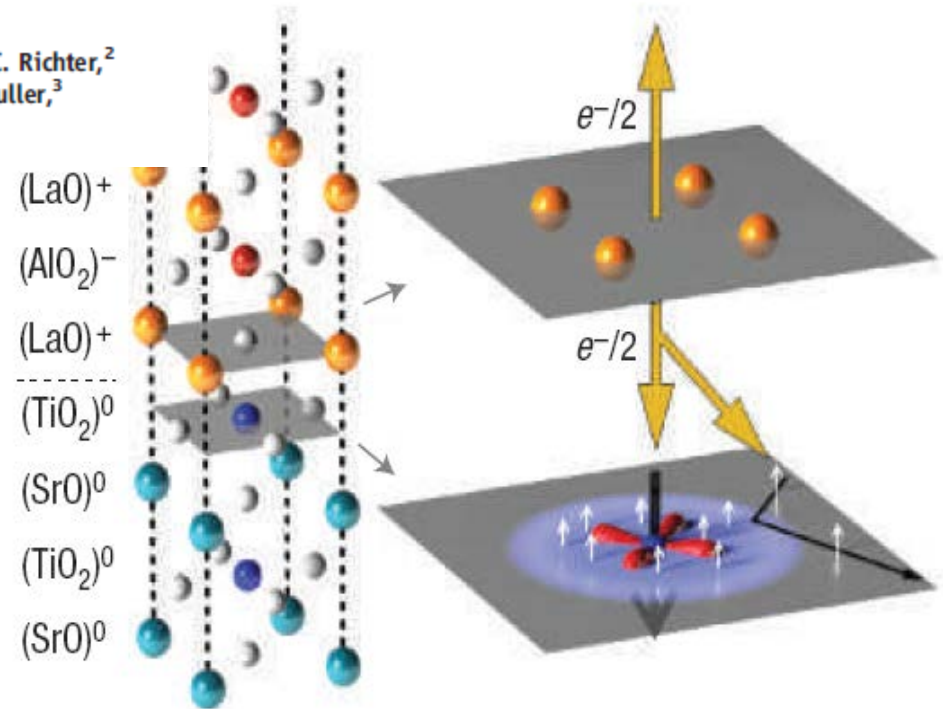
H. W. Hwang, *Science* 313, 1895 (2006)

Superconducting Interfaces Between Insulating Oxides

N. Reyren,¹ S. Thiel,² A. D. Caviglia,¹ L. Fitting Kourkoutis,³ G. Hammerl,² C. Richter,² C. W. Schneider,² T. Kopp,² A.-S. Rüetschi,¹ D. Jaccard,¹ M. Gabay,⁴ D. A. Müller,³ J.-M. Triscone,¹ J. Mannhart^{2*}



N. Reyren *et al.*, *Science* 317 1196 (2007)



A. Brinkman *et al.*, *Nature Materials* 6, 493 (2007)

LETTERS

Magnetic effects at the interface between non-magnetic oxides

A. BRINKMAN^{1*}, M. HUIJBEN^{1†}, M. VAN ZALK¹, J. HUIJBEN¹, U. ZEITLER², J. C. MAAN², W. G. VAN DER WIEL³, G. RIJNDERS¹, D. H. A. BLANK¹ AND H. HILGENKAMP¹

¹Faculty of Science and Technology and MESA* Institute for Nanotechnology, University of Twente, 7500 AE Enschede, The Netherlands

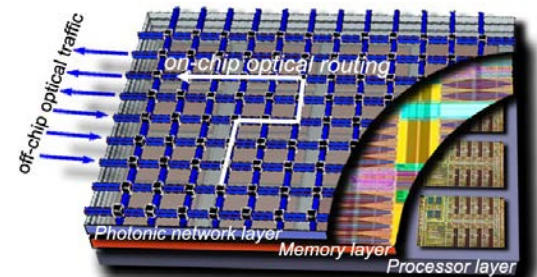
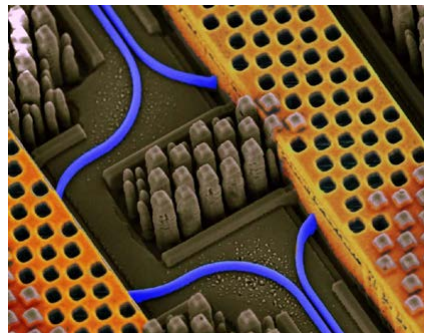
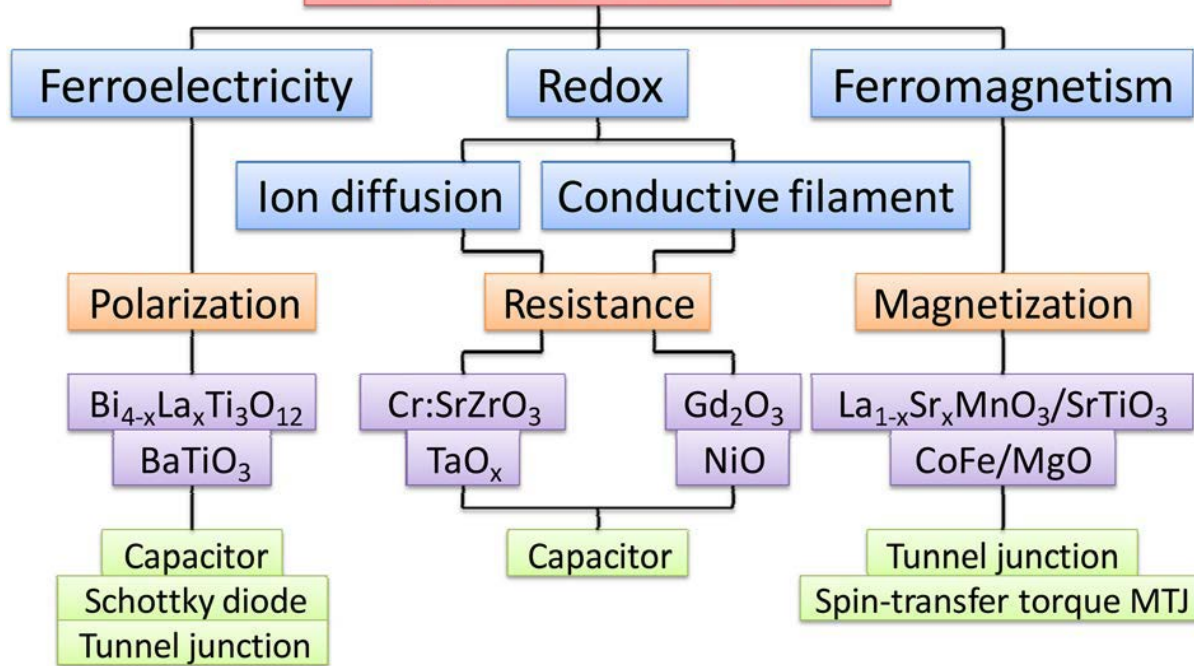
²High Field Magnet Laboratory, Institute for Molecules and Materials, Radboud University Nijmegen, 6525 ED Nijmegen, The Netherlands

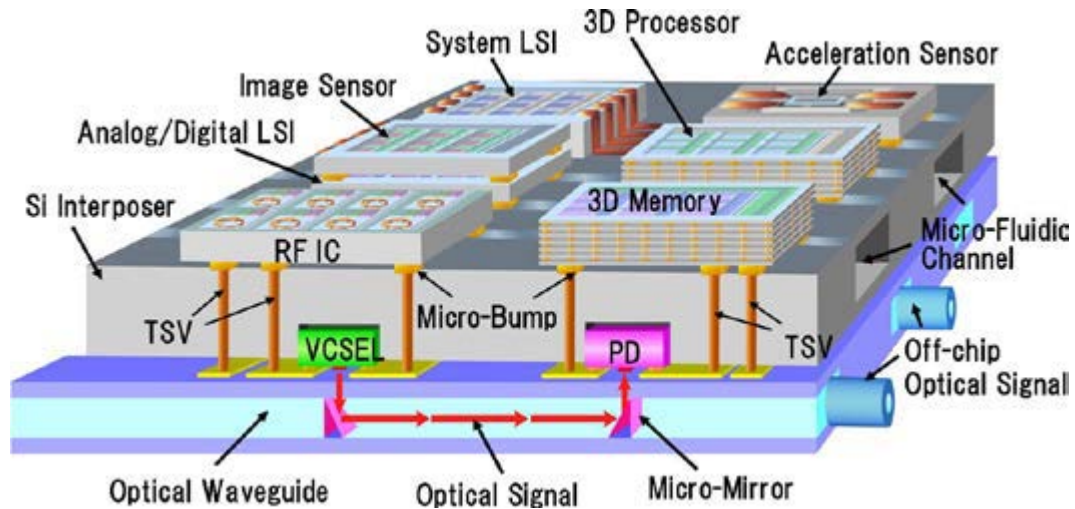
³Strategic Research Orientation NanoElectronics, MESA* Institute for Nanotechnology, University of Twente, 7500 AE Enschede, The Netherlands

[†]Present address: Physics Department, University of California, Berkeley, California 94720, USA

*e-mail: a.brinkman@utwente.nl

Adaptive oxide devices



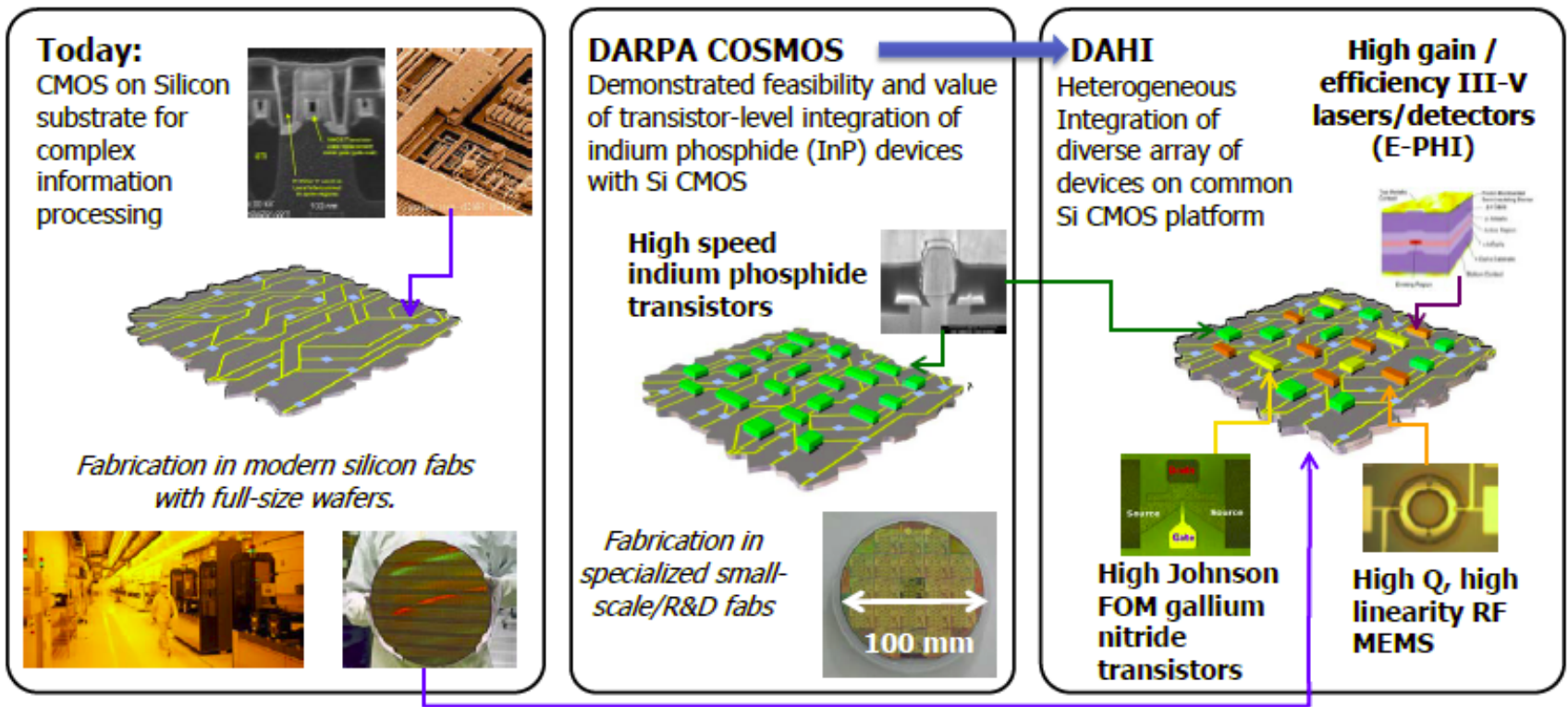


Conceptual structure of the 3-D heterogeneous optoelectronic integrated system-on-silicon for an intelligent vehicle system's variable signal-processing functions depending on the moving speed of the car.

K.-W. Lee, A. Noriki, K. Kiyoyama, T. Fukushima, T. Tanaka, and M. Koyanagi, *IEEE Trans. Electron Dev.* **58**, 748 (2011).

Diverse Accessible Heterogeneous Integration (DAHI):

- Compound Semiconductor Materials on Si,
- Electronic-photonic heterogeneous integration

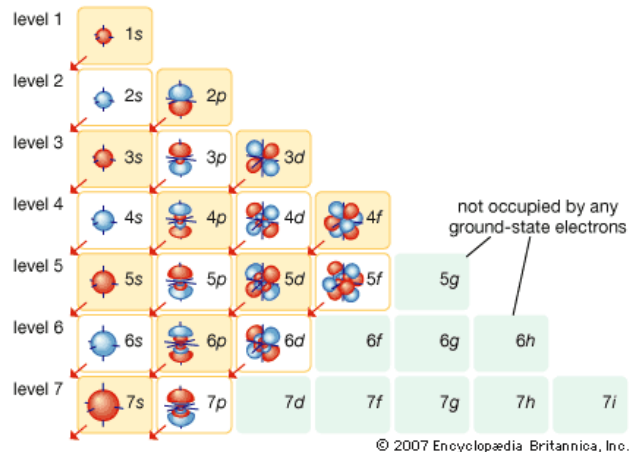


Transition metals

A transition metal is one which forms one or more stable ions which have *incompletely filled d orbitals*.

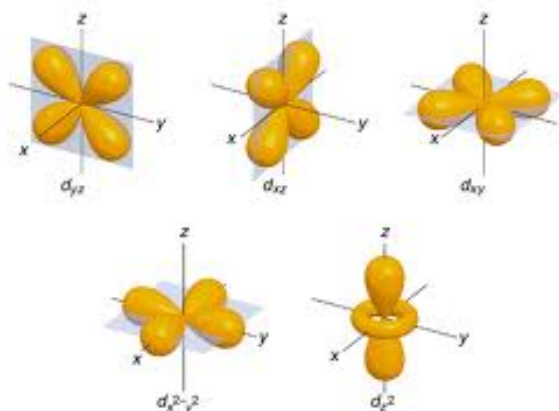


Erwin Schrödinger

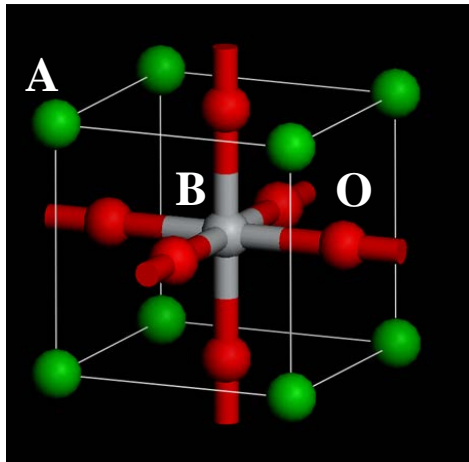


PERIODIC TABLE OF THE ELEMENTS

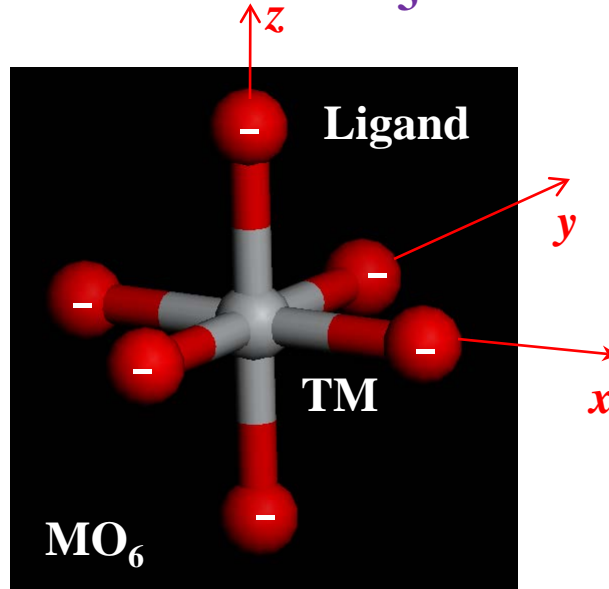
1	2	3	4	5	6	7	8	9	10	11	12	13	14	15	16	17	18	
H	He											B	C	N	O	F	Ne	
Li	Be											Al	Si	P	S	Cl	Ar	
Na	Mg											Zn	Ga	Ge	As	Se	Br	Kr
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr	
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe	
Cs	Ba		Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn	
Fr	Ra		Rf	Db	Sg	Bh	Hs	Mt	Ds	Rh	Cn	Uut	Uuq	Uup	Uuq	Uuh	Uuo	
			La	Ce	Pr	Nd	Pm	Sm	Eu	Gd	Tb	Dy	Ho	Er	Tm	Yb	Lu	
			Ac	Th	Pa	U	Np	Pu	Am	Cm	Bk	Cf	Es	Fm	Md	No	Lr	



Perovskite oxides ABO_3

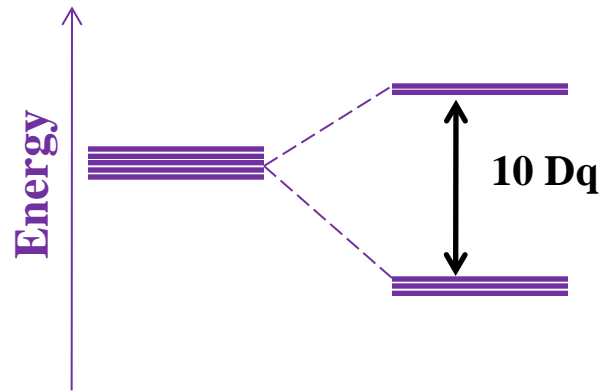


$CaTiO_3$, $BaTiO_3$, $SrHfO_3$,...

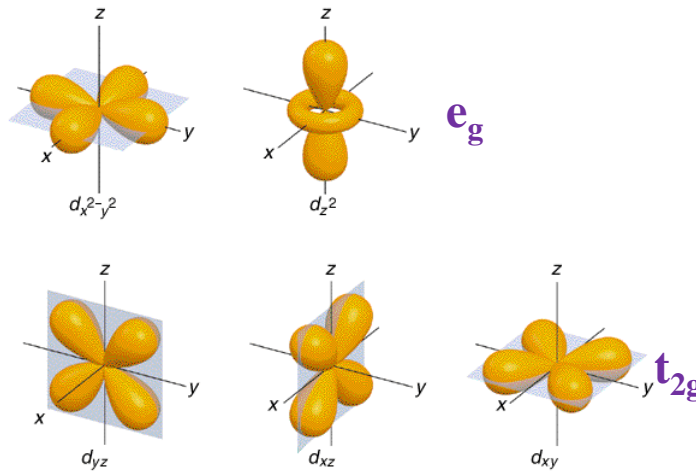


Count Lev Alekseevich Perovski
1792-1856

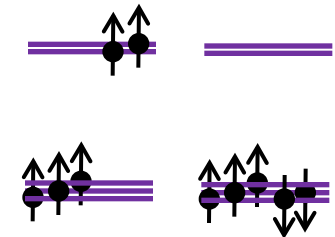
Octahedral symmetry (O_h):



Ligand field theory

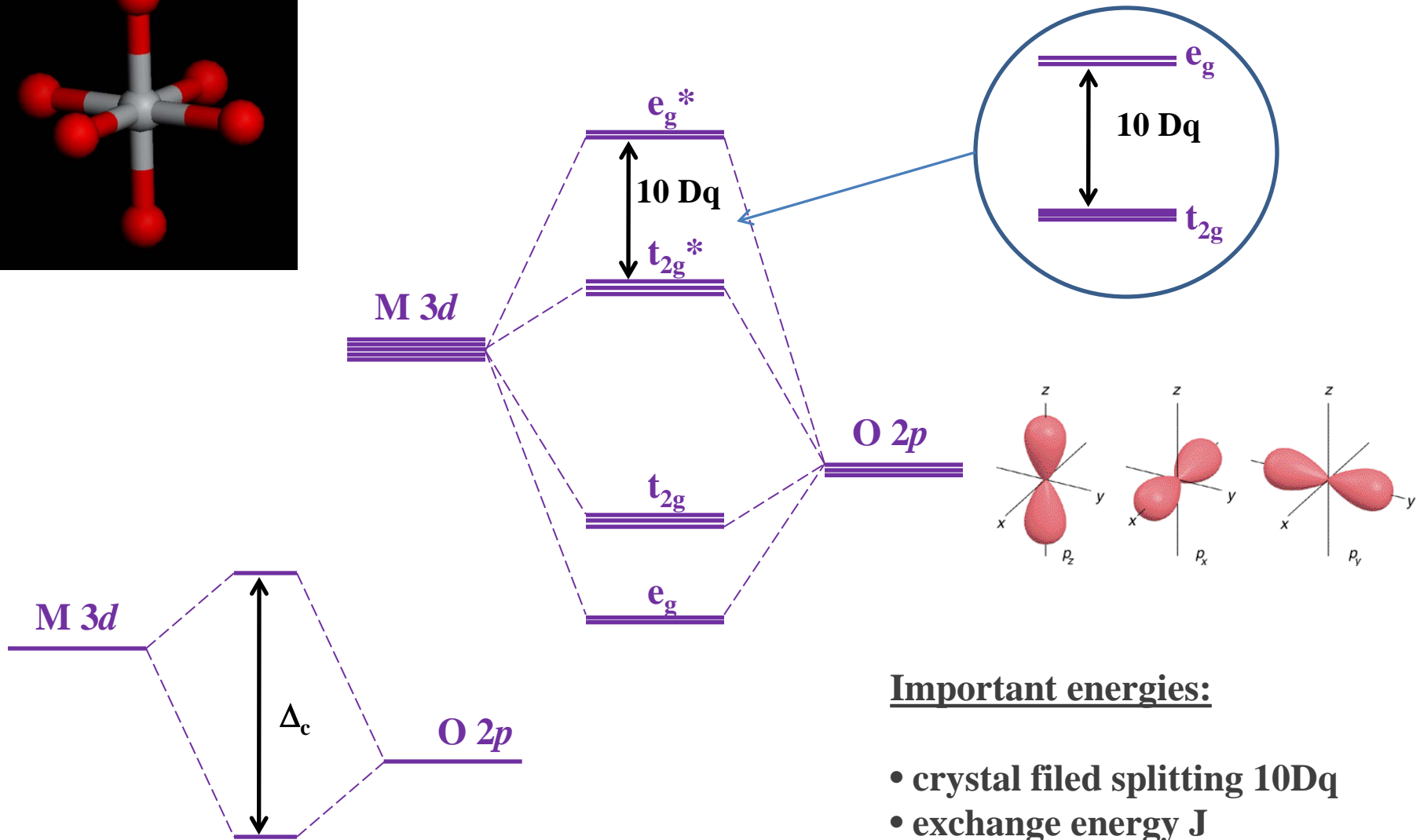
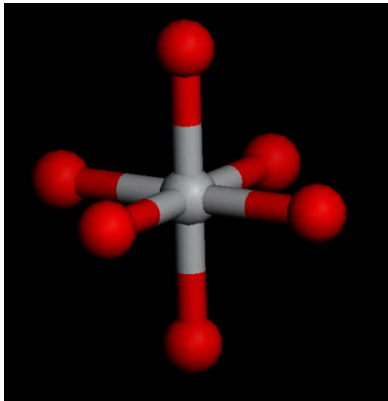


High spin Low spin
 Fe^{3+} (d^5)



$$E^S - E^T = 2J$$

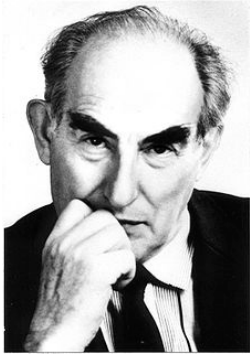
Molecular Orbital Theory



Important energies:

- crystal field splitting $10Dq$
- exchange energy J
- charge transfer energy Δ_c

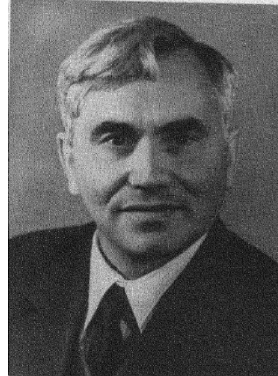
Ferroelectricity



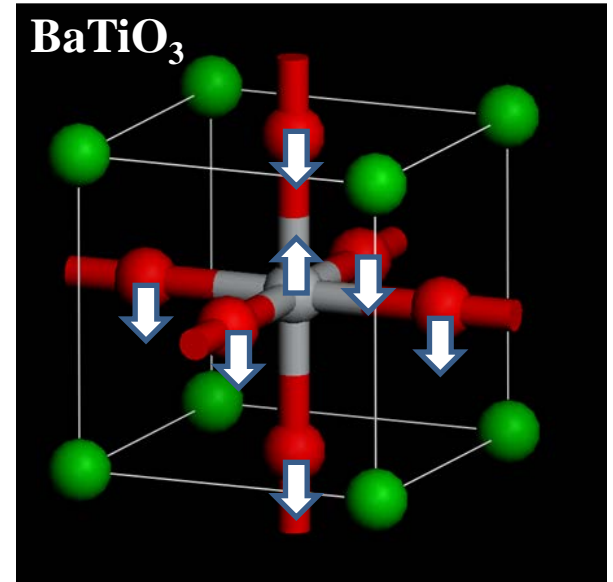
V.L. Ginzburg
1916-2009



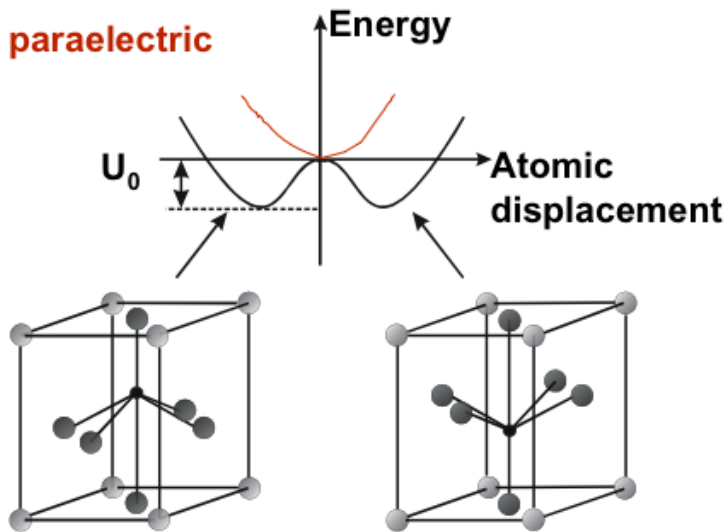
L.D. Landau
1908-1968



B.M. Vul
1903-1985



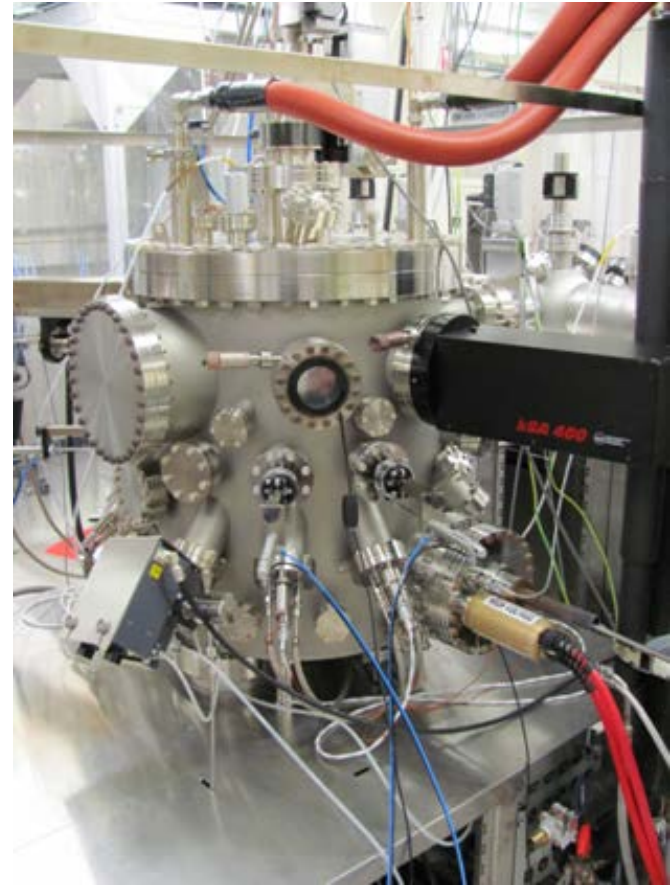
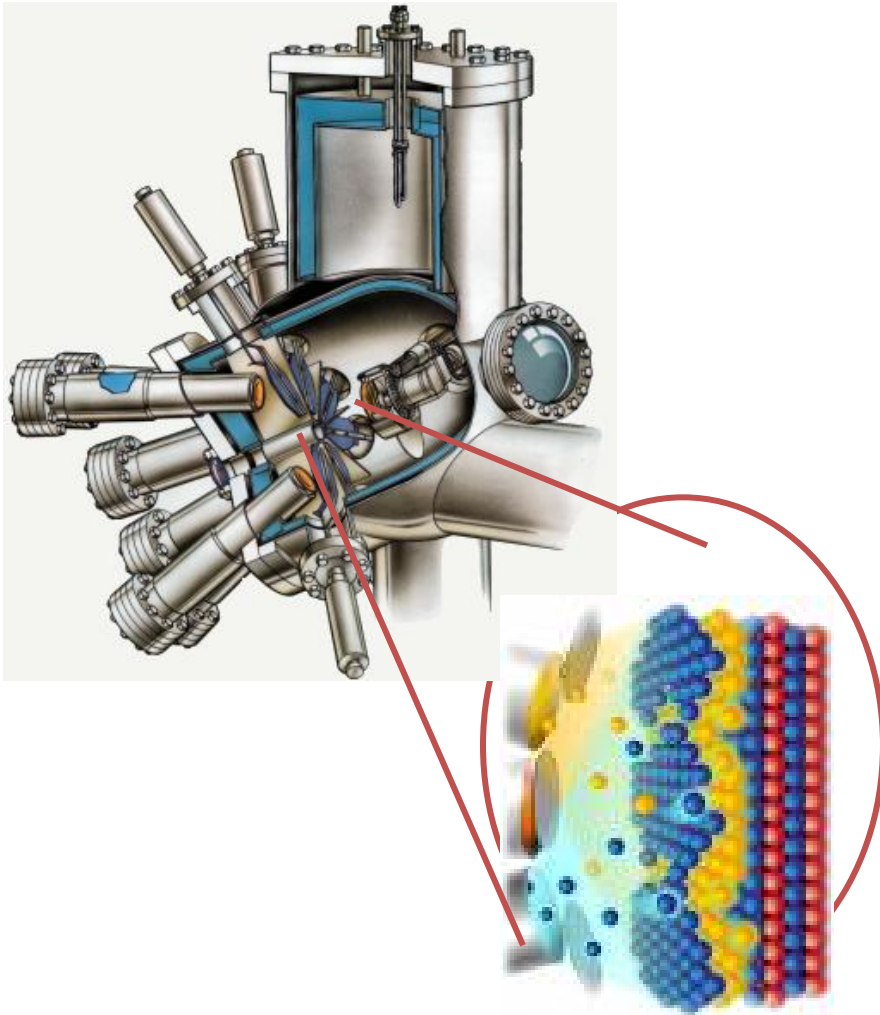
paraelectric



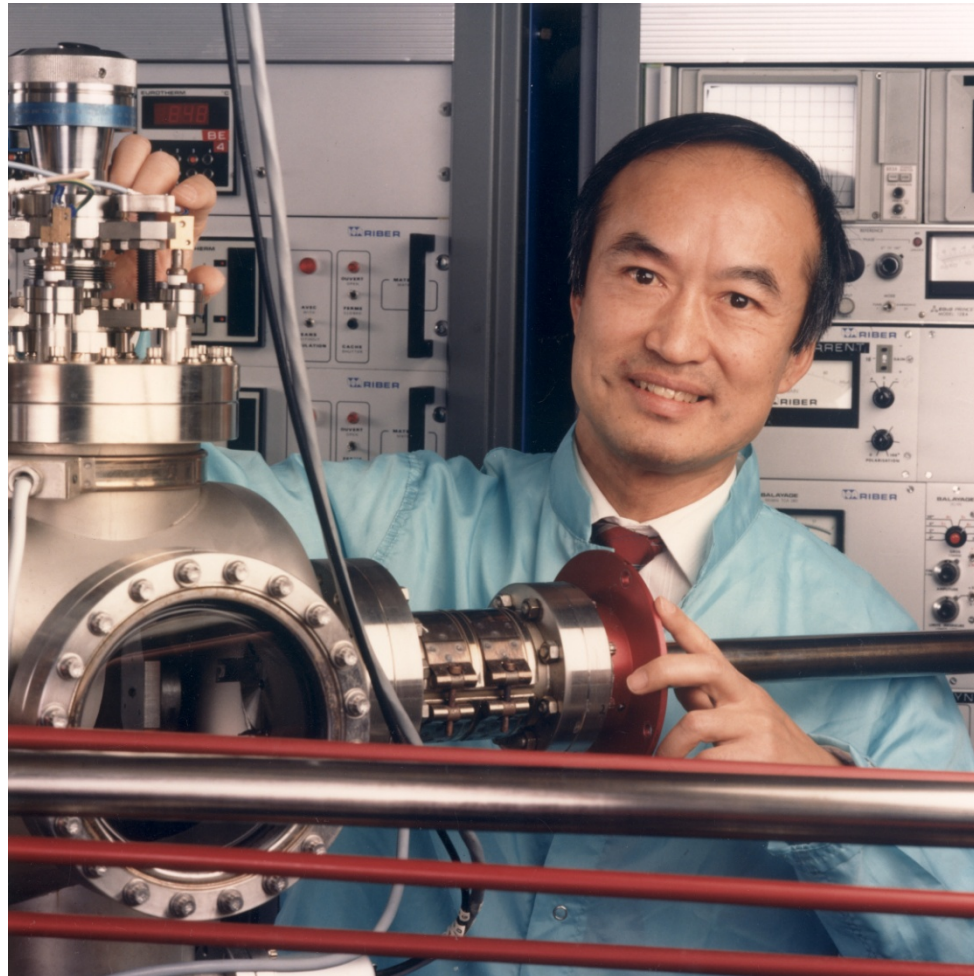
$$\Delta E = \frac{1}{2}\alpha_0 (T - T_0) P_x^2 + \frac{1}{4}\alpha_{111} P_x^4 + \frac{1}{6}\alpha_{1111} P_x^6$$

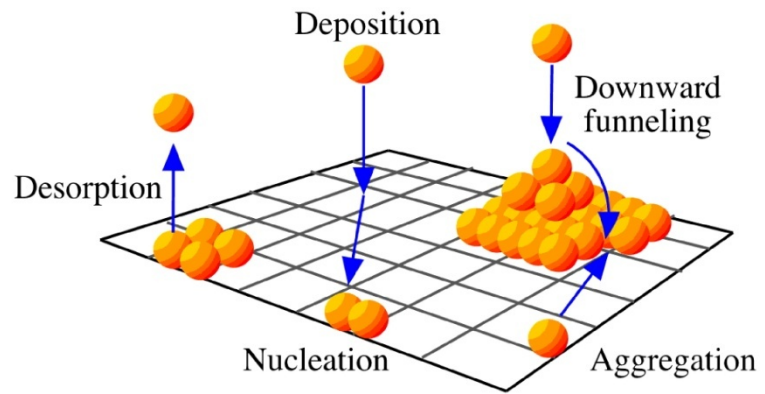
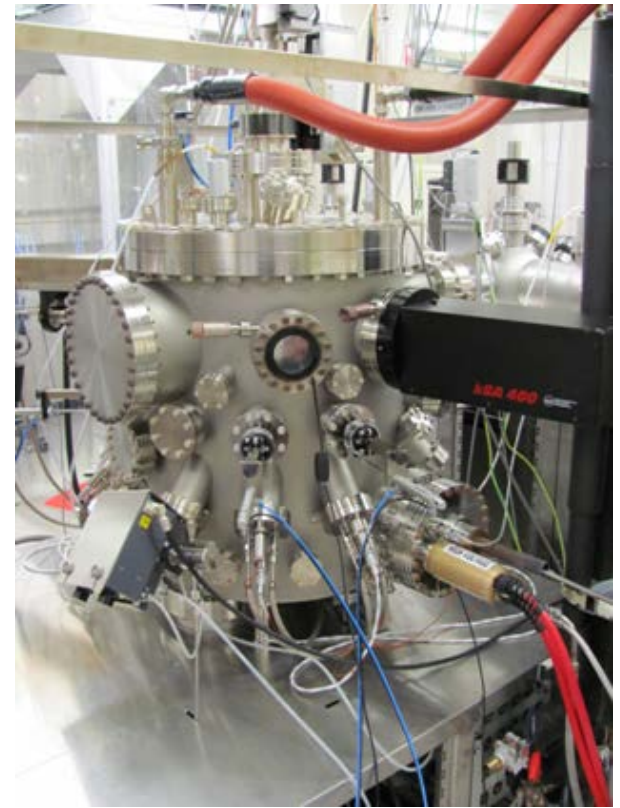
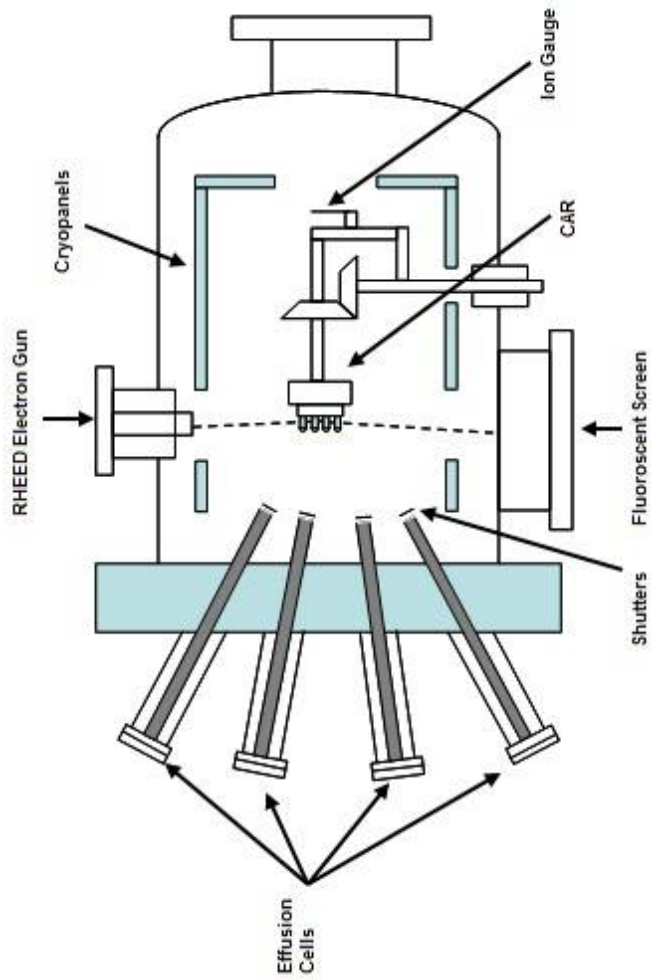
Molecular Beam Epitaxy

Epitaxy: ordered growth on a monocrystalline substrate
From two Greek words: “epi”-above and “taxis”-in ordered manner

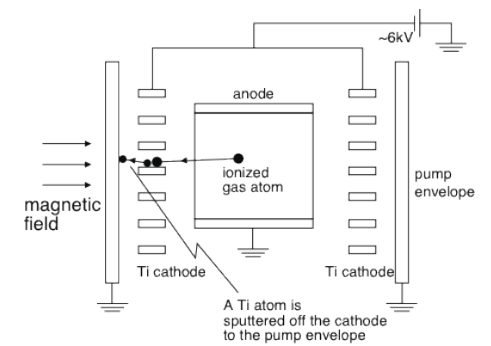
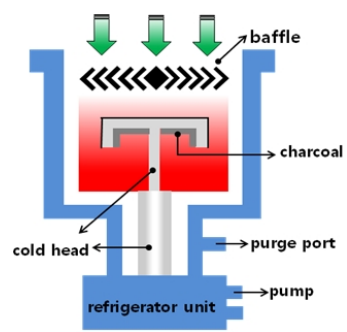


**MBE was invented in the late 1960s at Bell Laboratories
by J. R. Arthur and Alfred Y. Cho**





Making Nothing: Vacuum Pumps



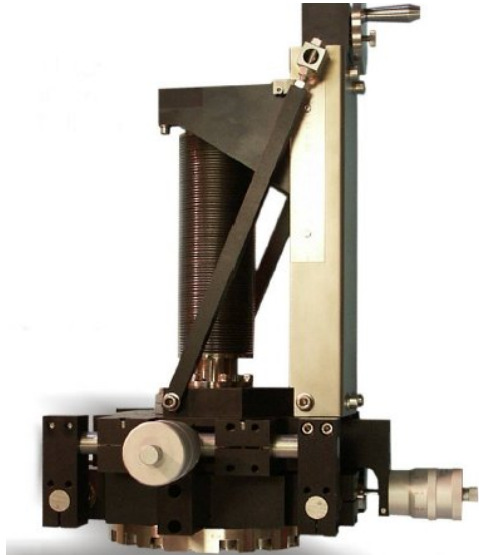
Vacuum Chamber



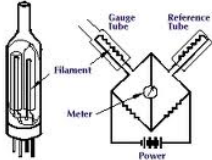
Flanges



Manipulators



Vacuum gauges



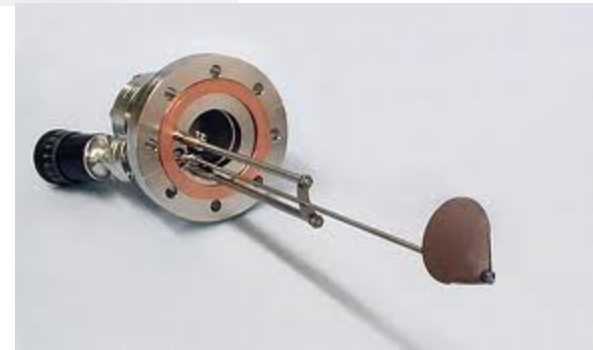
Transfer rods



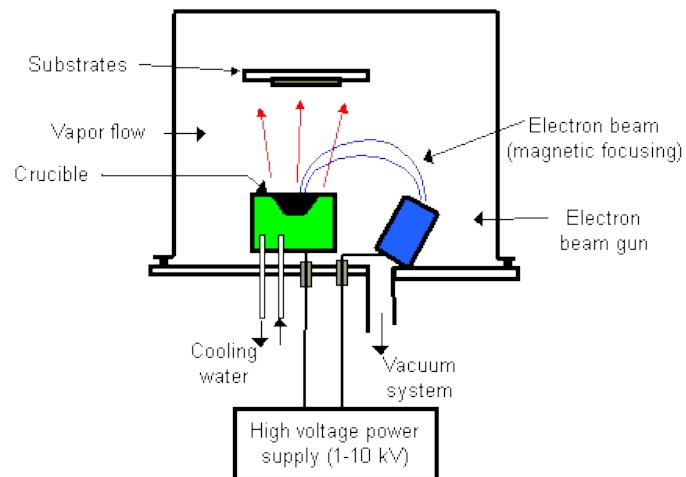
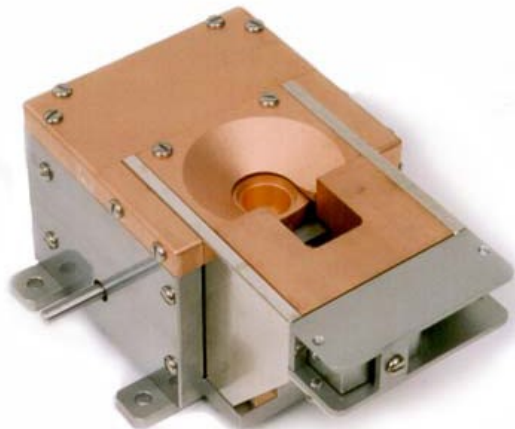
Knudsen Cell



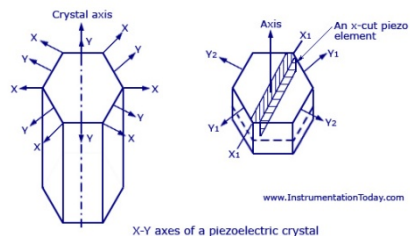
Martin Hans Christian Knudsen (1871 -1949)



E-gun evaporator



Quartz Crystal Monitor

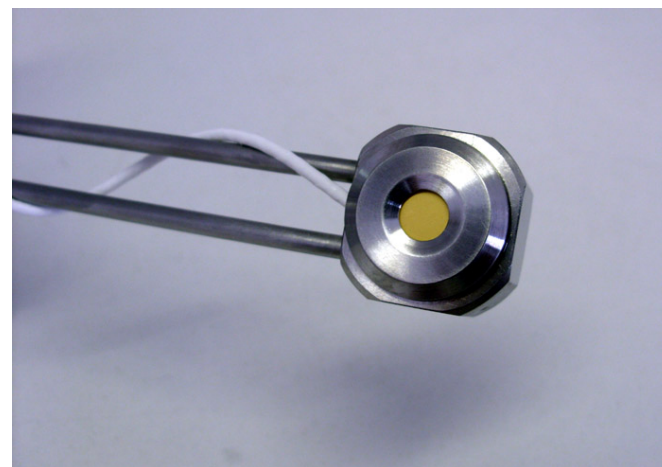
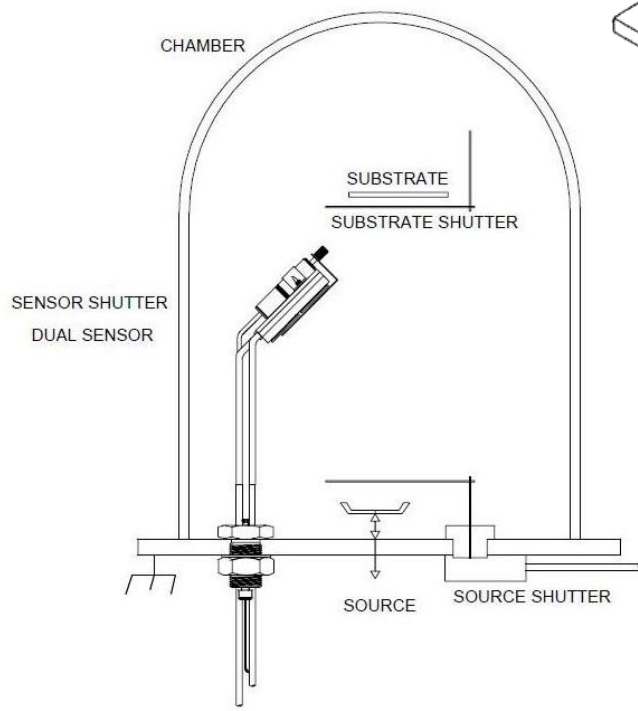
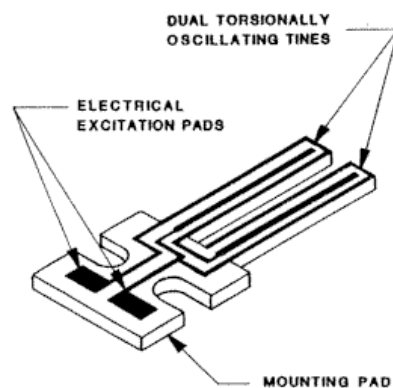
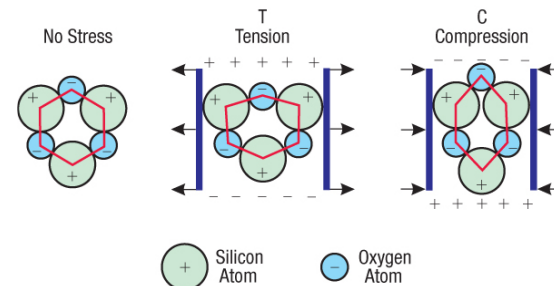


Jacques Curie

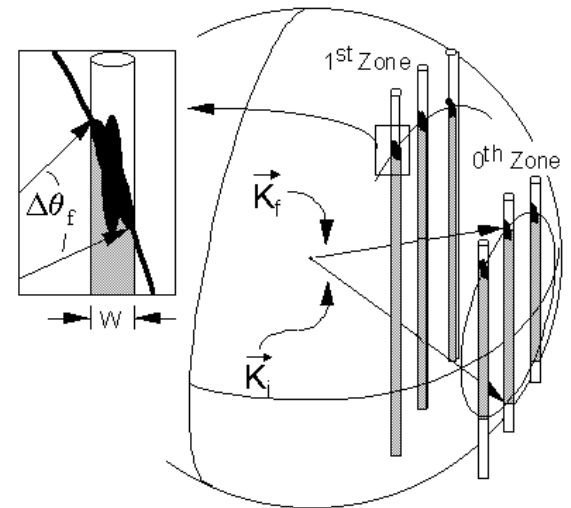
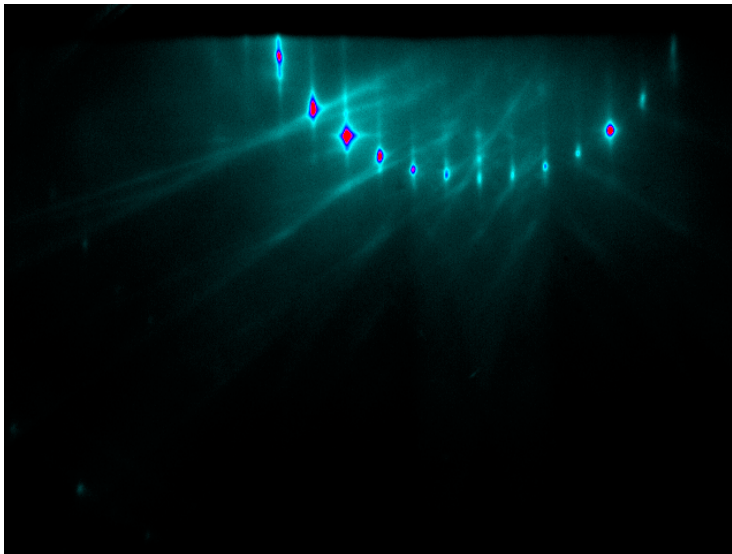
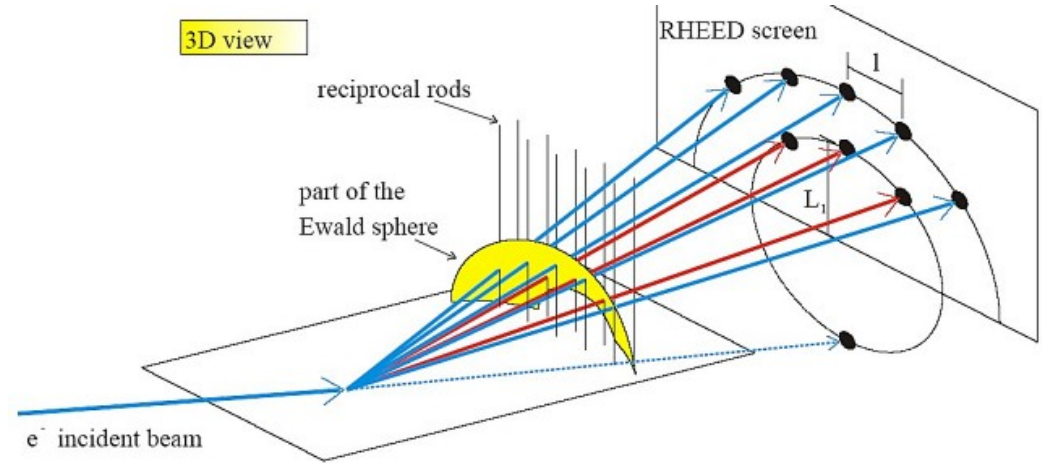
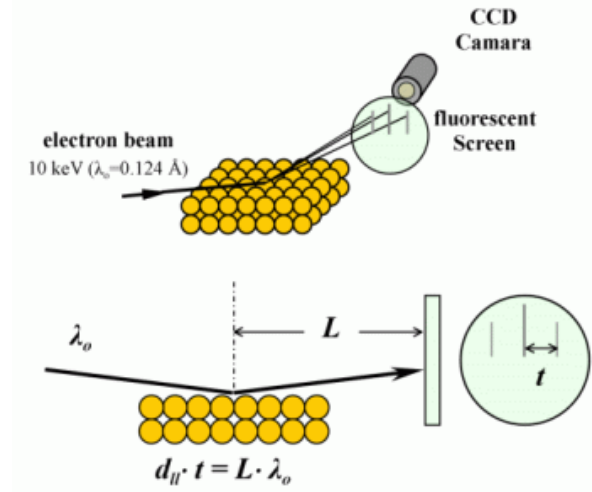


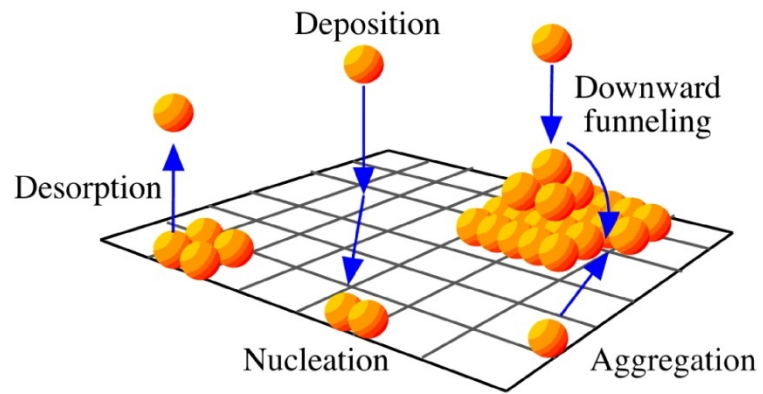
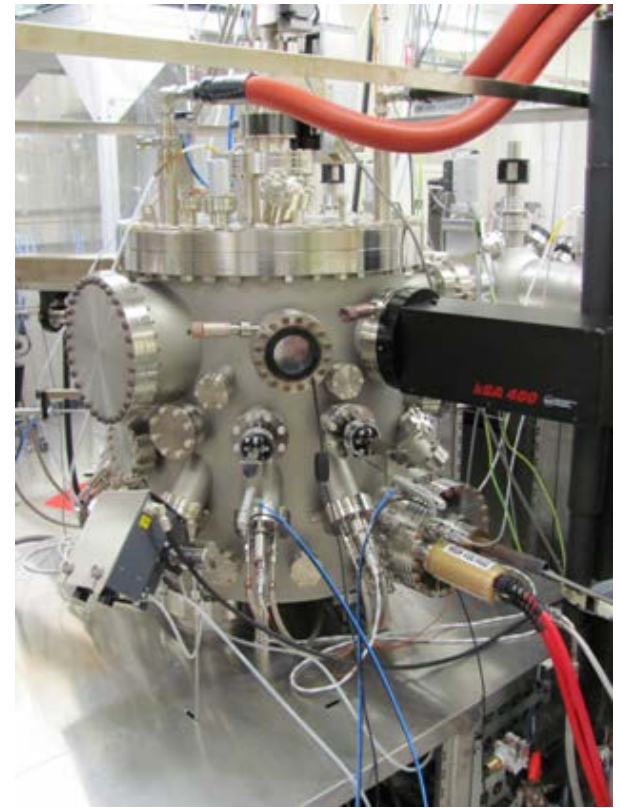
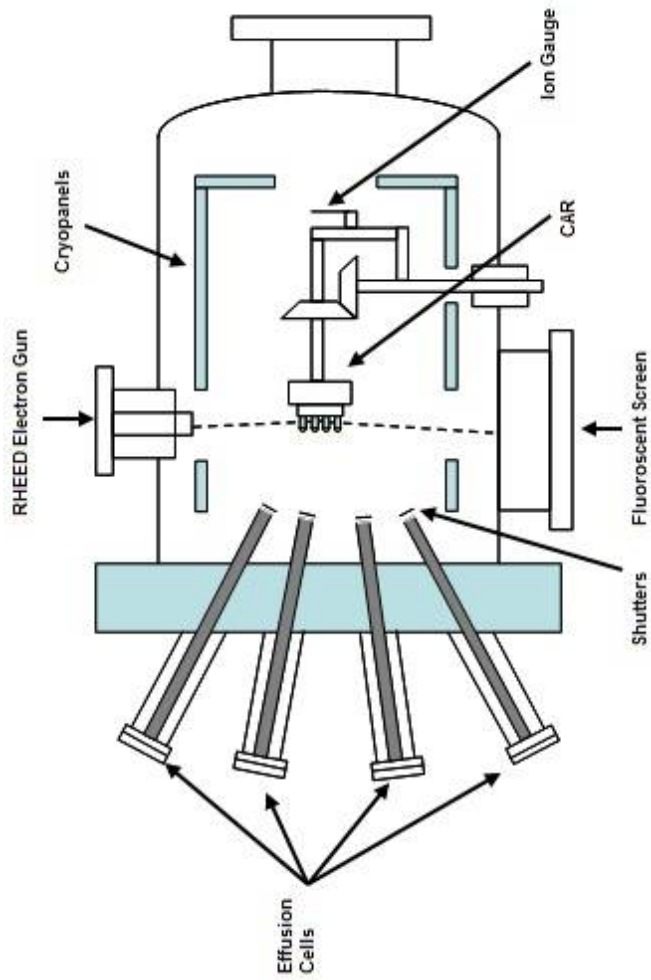
Pierre Curie

Piezoelectric Effect in Quartz

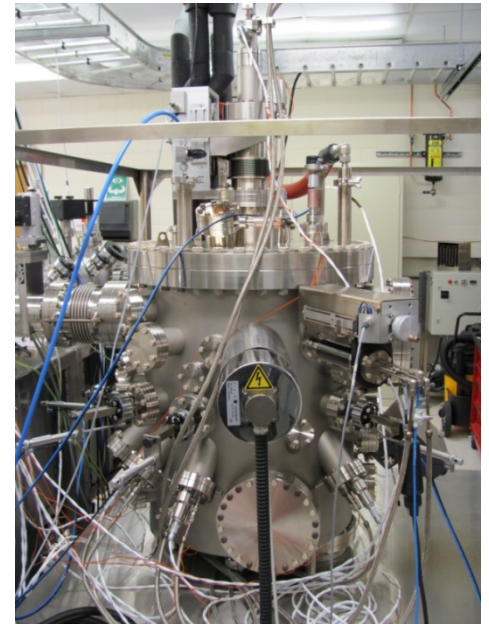
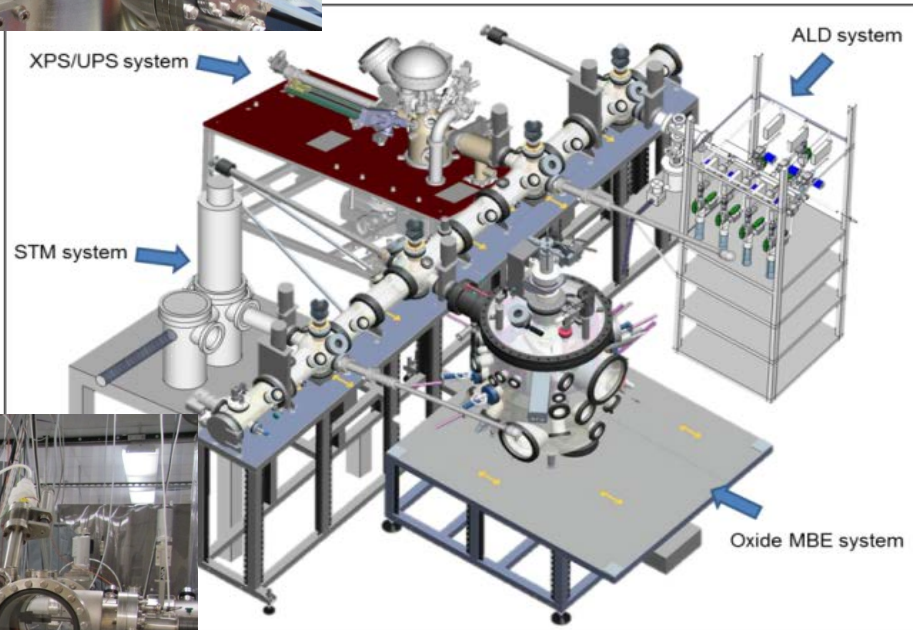
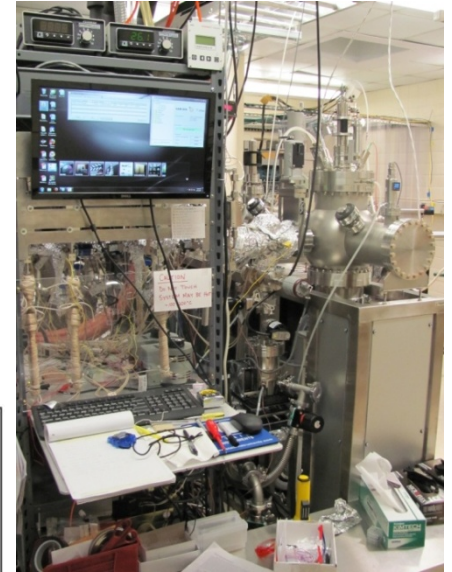
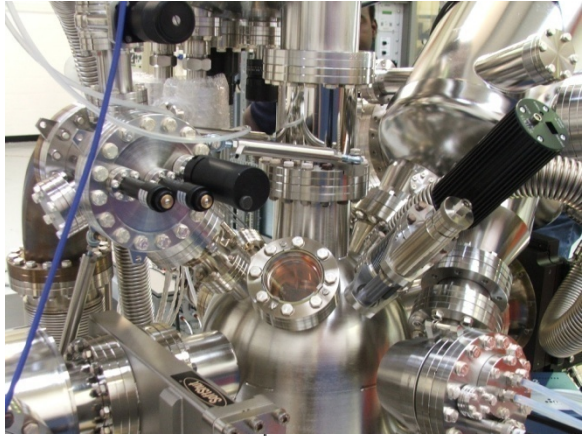


RHEED





Materials Physics Laboratory



Theoretical methods



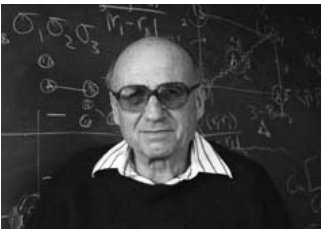
$$\left(-\frac{\hbar^2 \nabla^2}{2m} + V(r) \right) \psi_i(r) = \varepsilon_i \psi_i(r)$$



$$\Psi(\mathbf{R}, \mathbf{r}) = \sum_{k=1}^K \chi_k(\mathbf{r}; \mathbf{R}) \phi_k(\mathbf{R}),$$

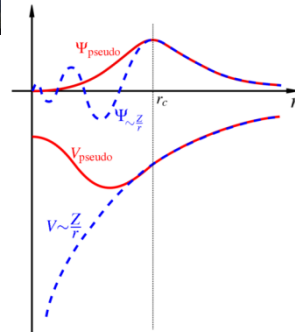
$$H_e \chi(\mathbf{r}) = E_e \chi(\mathbf{r})$$

$$[T_n + E_e(\mathbf{R})] \phi(\mathbf{R}) = E \phi(\mathbf{R})$$

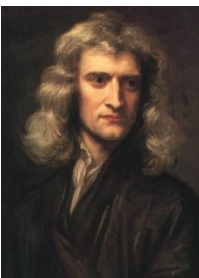


$$E_{KS}[n] = \langle \Psi | \hat{H} | \Psi \rangle = E_{K.E}[n] + E_{Hartree}[n] + E_{elec-ion}[n] + E_{ion-ion} + E_{XC}[n]$$

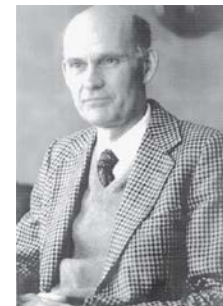
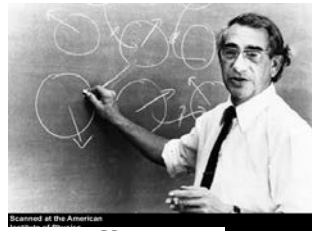
$$\left(-\frac{\hbar^2 \nabla^2}{2m} + V_{KS}(r) \right) \psi_i(r) = \varepsilon_i \psi_i(r)$$



$$V_{KS}(r) = V_{ext}(r) + \int \frac{n(r')}{|r-r'|} dr' + V_{XC}(r)$$



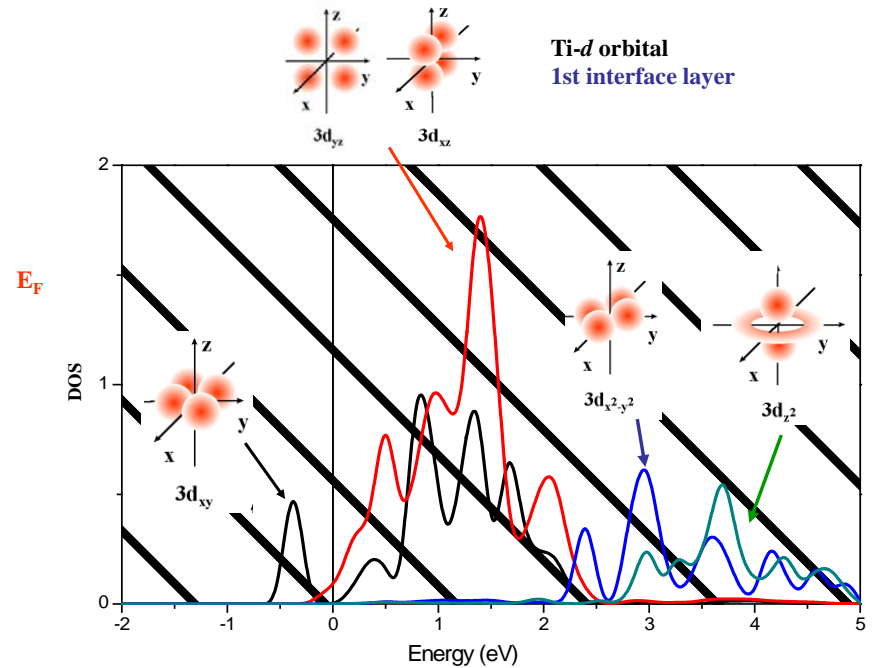
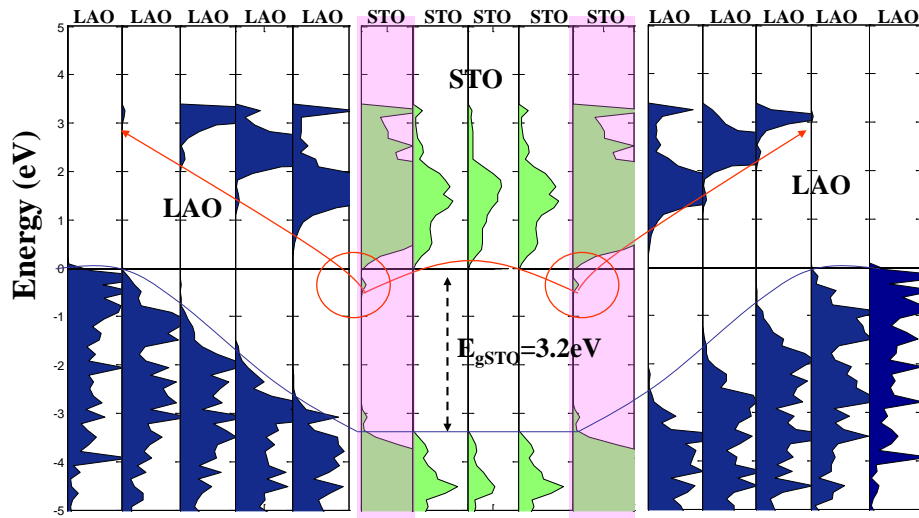
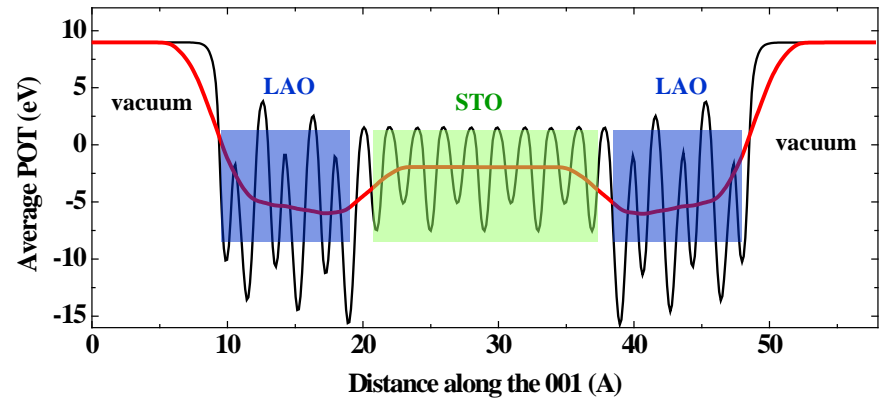
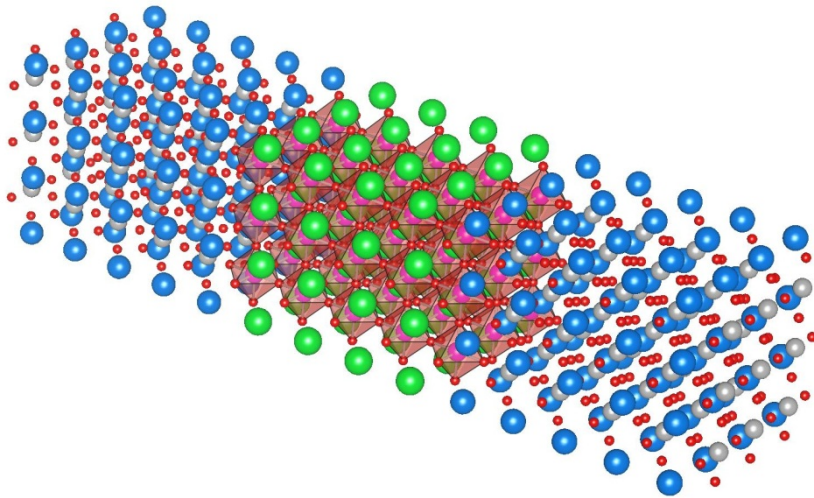
$$F_i = -\frac{\partial E}{\partial R_i} \longrightarrow F_i = m_i \ddot{x}_i$$



$$H = -t \sum_{\langle i,j \rangle, \sigma} c_{i,\sigma}^\dagger c_{j,\sigma} + U \sum_{i=1}^N n_{i\uparrow} n_{i\downarrow}$$

$$E_i = \varepsilon_i + \langle \Phi_i | \Sigma(E_i) - V_{xc} | \Phi_i \rangle \approx \varepsilon_i + Z_i \langle \Phi_i | \Sigma(\varepsilon_i) - V_{xc} | \Phi_i \rangle$$

SrTiO₃/LaAlO₃ heterostructure:

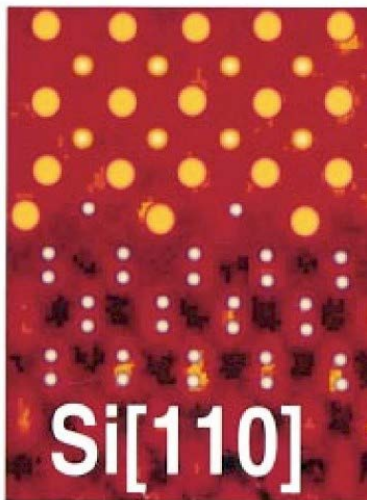


COX: Crystalline oxide on semiconductor

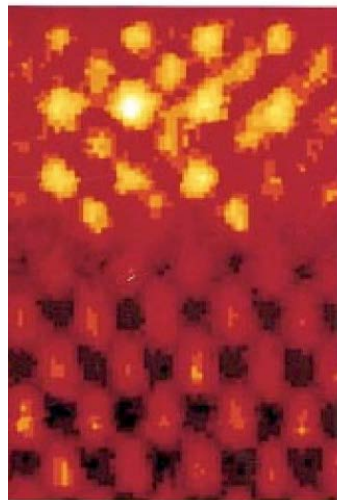


SrTiO₃ on Si

Model



Experiment



BaTiO₃ on Ge

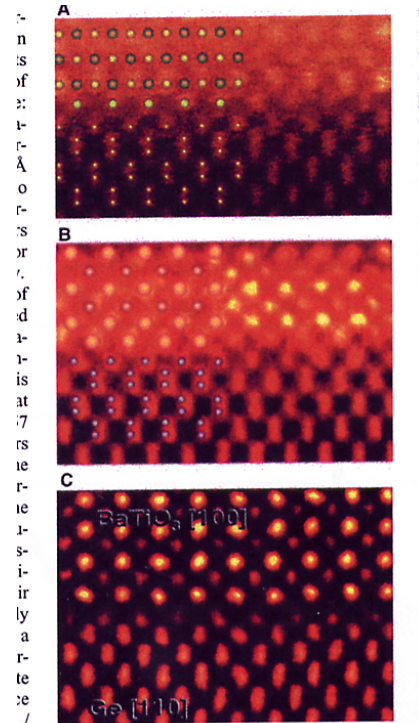


Fig. 1. Alkaline earth and perovskite oxide heteroepitaxy on silicon and germanium. The figure illustrates our ability to manipulate interface structure at the atomic level using our (AO)_n(A'BO₃)_m structure series. The n/m ratio defines the electrical characteristics of this new physical system of COS in a MOS capacitor. In (A), $n = 3, m = 0$; in (B), $n = 1, m = 2$; in (C), $n = 0, m = 3$.

R. McKee, F. Walker, M. Chisholm, *PRL* 81 3014 (1998)
R. McKee, F. Walker, M. Chisholm, *Science* 293, 468 (2001)

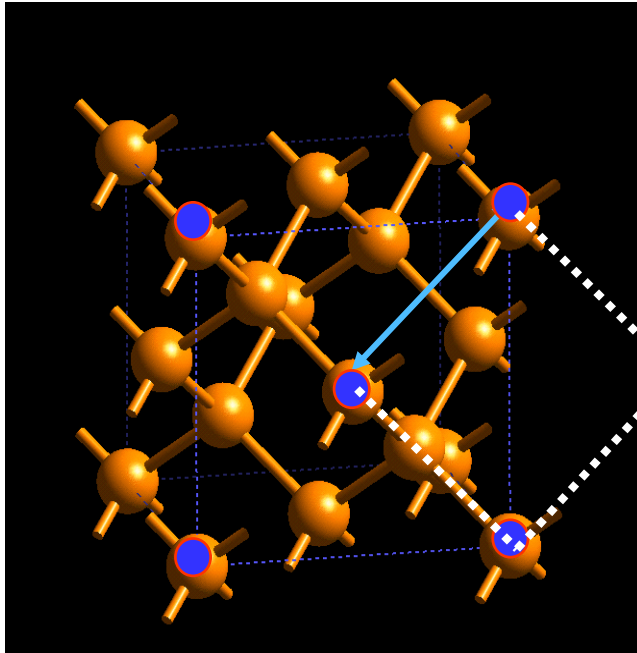
Si and STO are very different!

A. Geometry:

Silicon

45 ° “rotation”

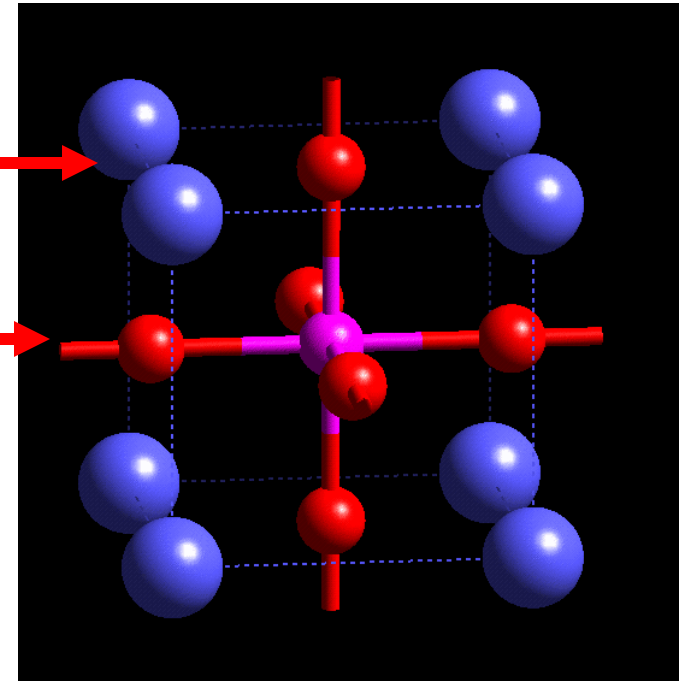
ABO₃



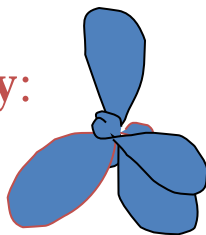
A-layer

B-layer

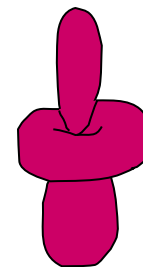
$$a_{\text{Si}}/(2)^{0.5}=3.84 \text{ \AA}$$
$$a_{\text{STO}}=3.905 \text{ \AA}$$



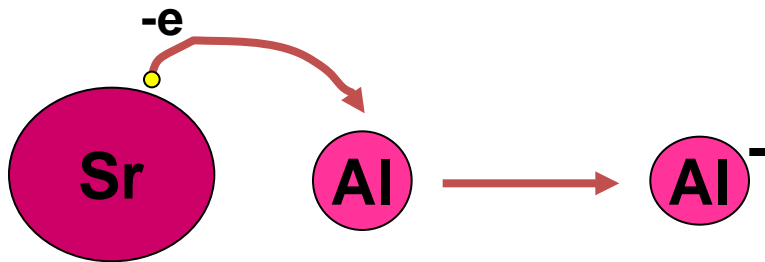
B. Chemistry:



?



Zintl intermetallics : SrAl_2

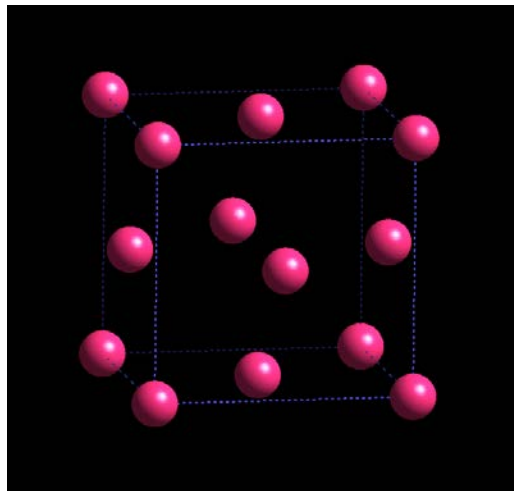


	13	14	15
Al	Si	P	

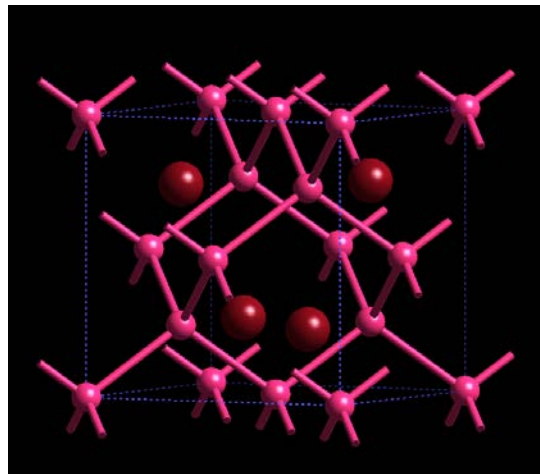
Zintl Alchemy



fcc Al metal

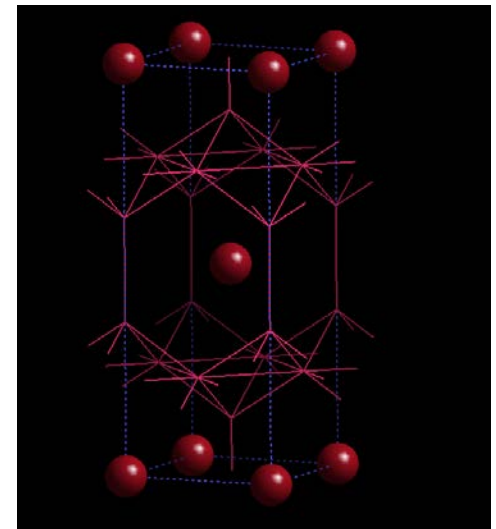


SrAl_2 structure



Edward Zintl (1898-1941)

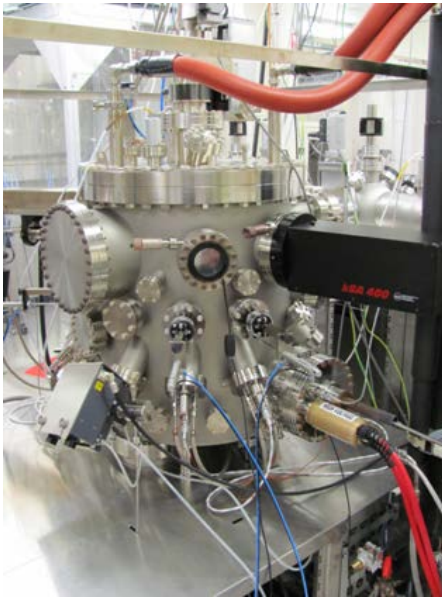
tI10 SrAl_4 structure



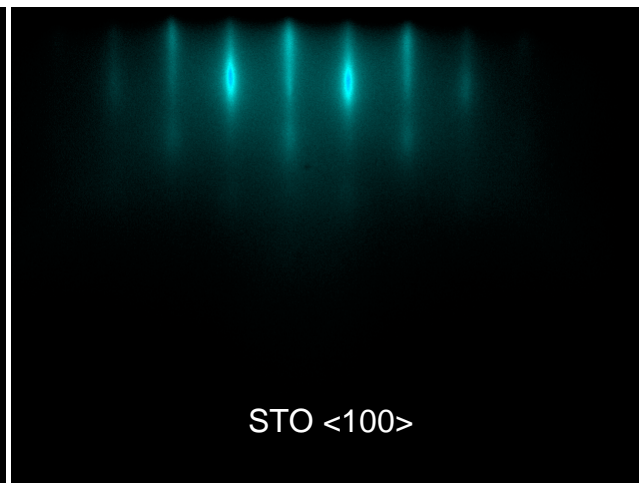
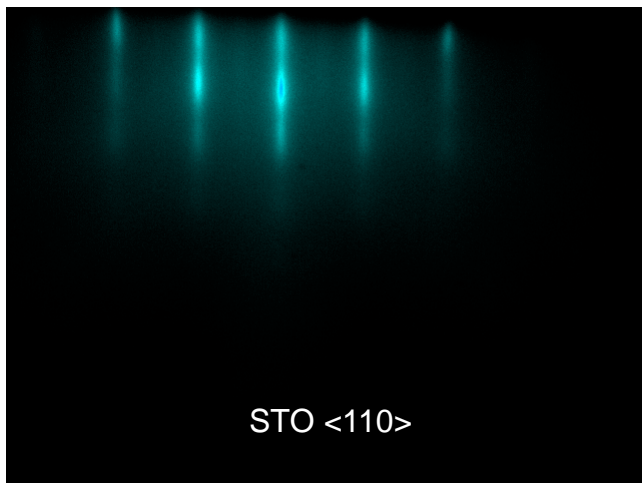
SrTiO₃ deposition on Si

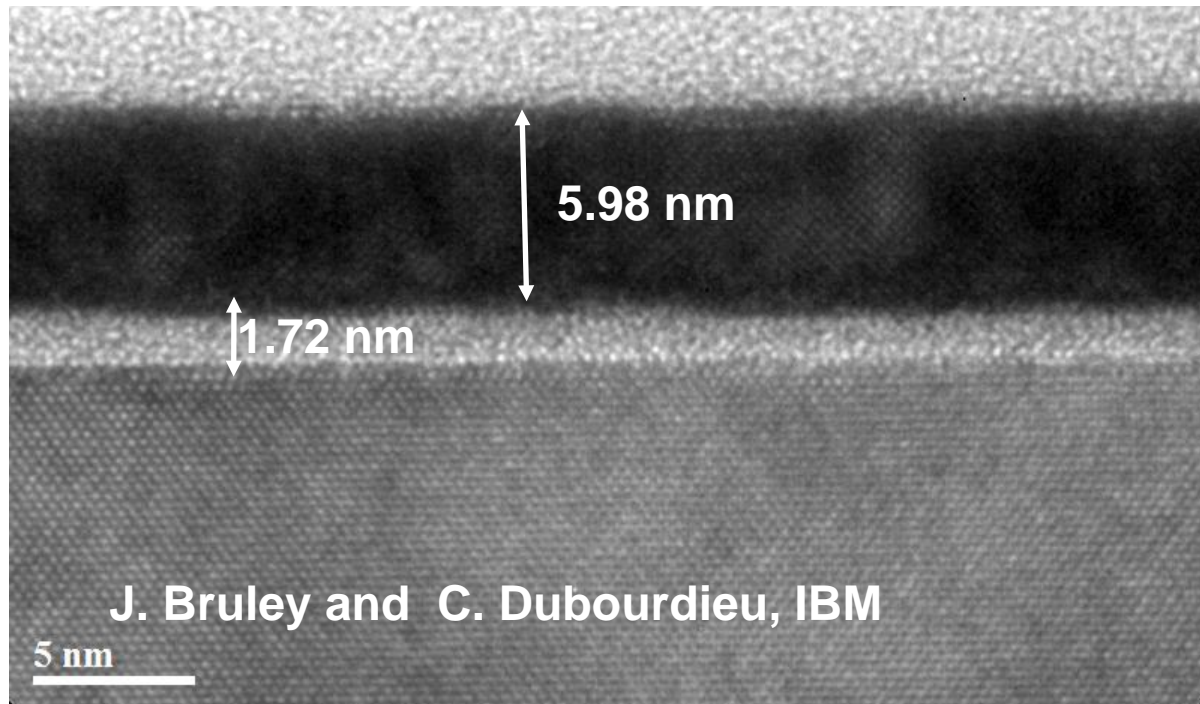
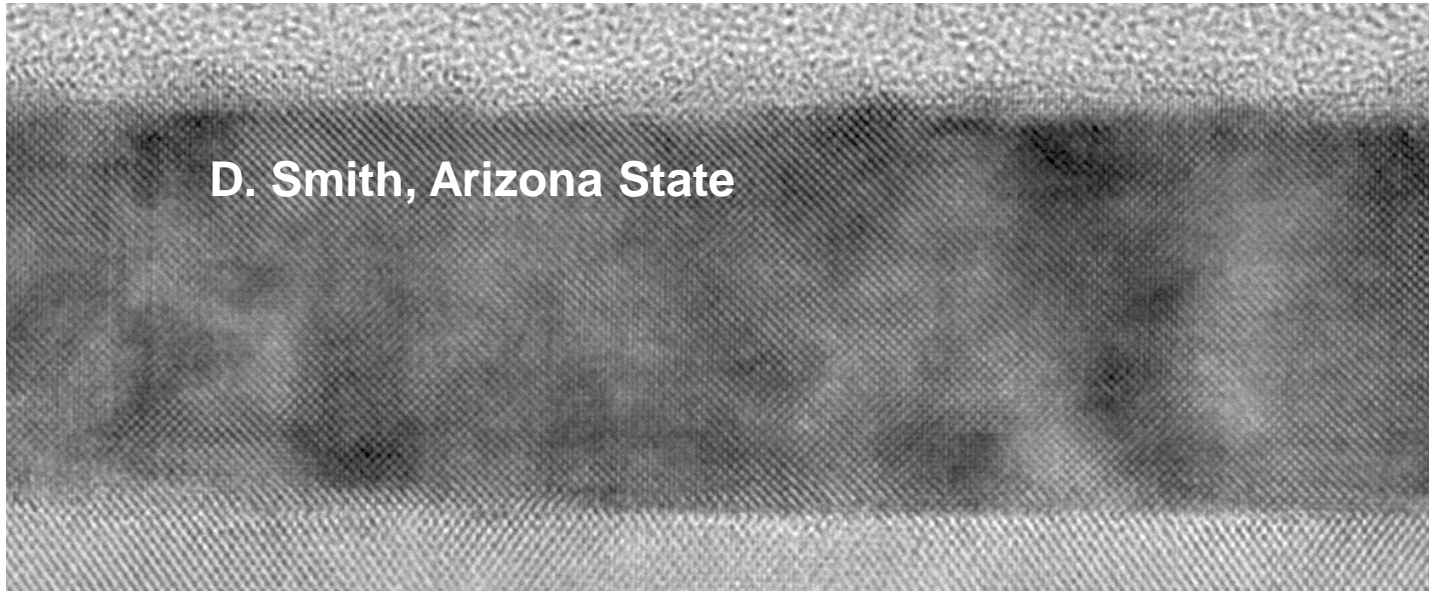


Edward Zintl
1898-1941

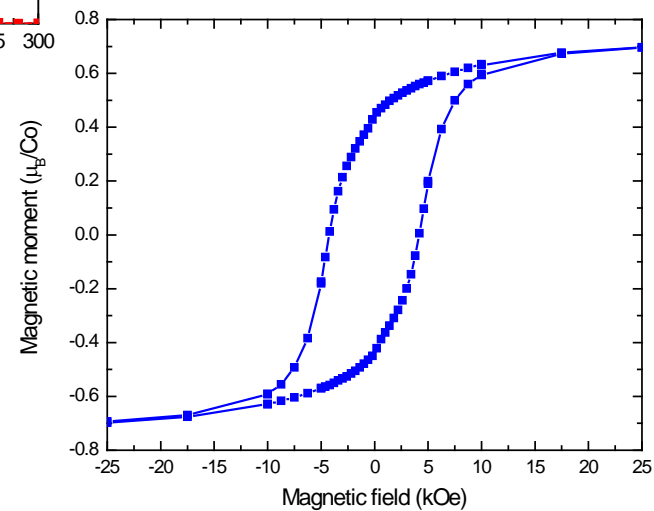
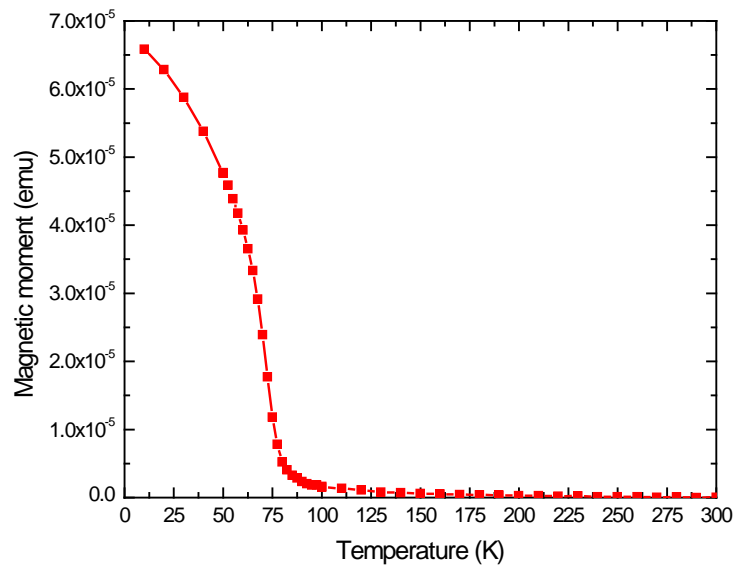
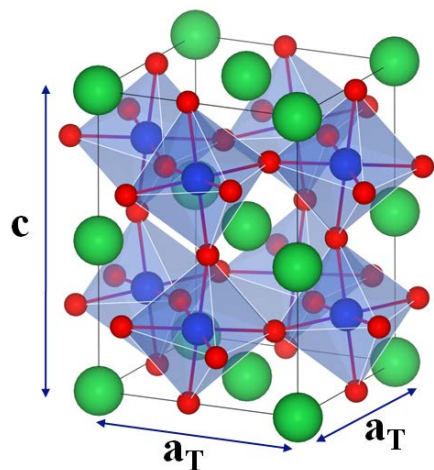


- Sr-assisted SiO₂ desorption
Y. Wei et al., J. Vac. Sci. Technol. B **20**, 1402 (2002).
B. K. Moon and H. Ishiwara, Jpn. J. Appl. Phys., Part 2 **33**, L472 (1994).
- ½ monolayer Sr on Si
(Zintl template layer)
- Initial amorphous SrTiO₃ seed layer at 200°C (4 unit cells)
Crystallize at 550°C
- Main SrTiO₃ deposition
4x10⁻⁷ torr O₂ at 550°C
Co-evaporation of Sr and Ti at 1 monolayer per minute
20 unit cells (fully relaxed)





Integrating ferromagnets on Si (001)



Properties and applications $\text{La}_{1-x}\text{Sr}_x\text{CoO}_3$

- Properties

- $\text{Co}^{3+} : 3d^6$
- 0.6 eV gap semiconductor
- Non-magnetic at low temperature but paramagnetic at room temperature
- **Epitaxial strain induces ferromagnetism***
- Spin state transitions
 - Low, intermediate, high-spin
- Metal-insulator transition when doped

- Possible applications

- Electrode (Sr-doped)
 - Cathode material for solid oxide fuel cells
 - Epitaxial oxide electrode for perovskite multilayers
- Gas sensors / catalysis
- Magnetic semiconductor
 - Spintronics

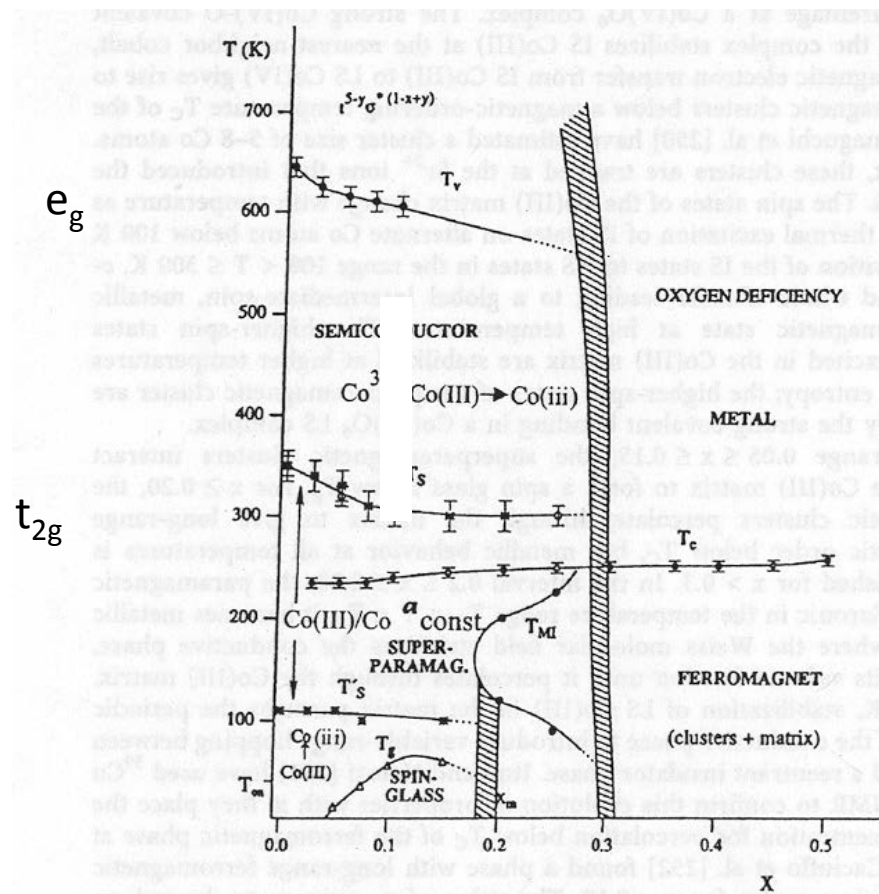
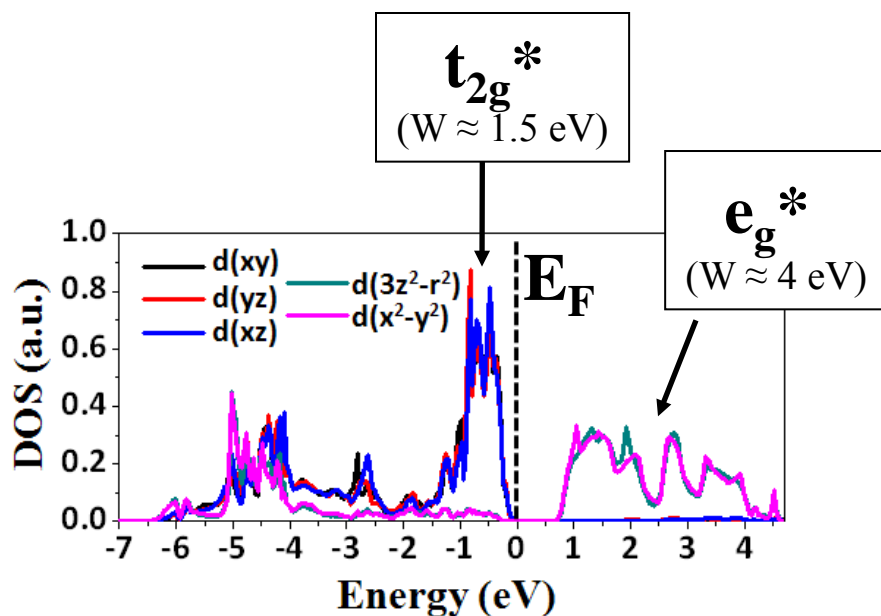
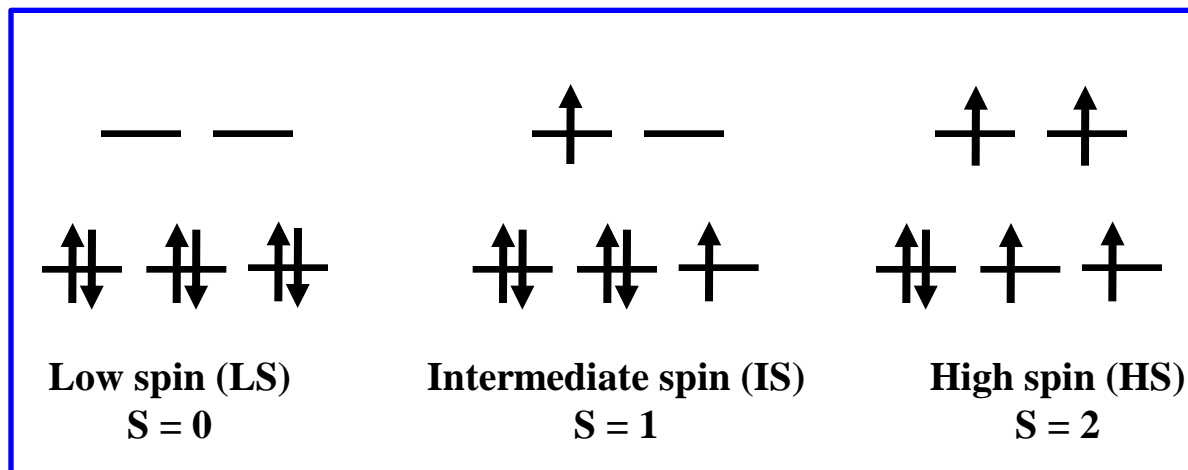
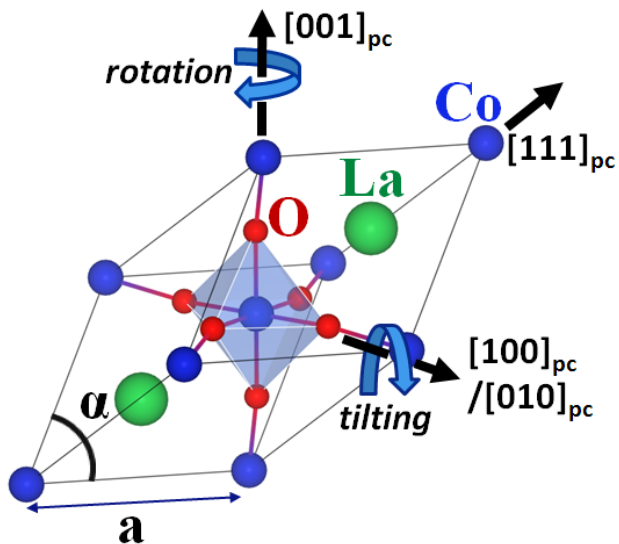


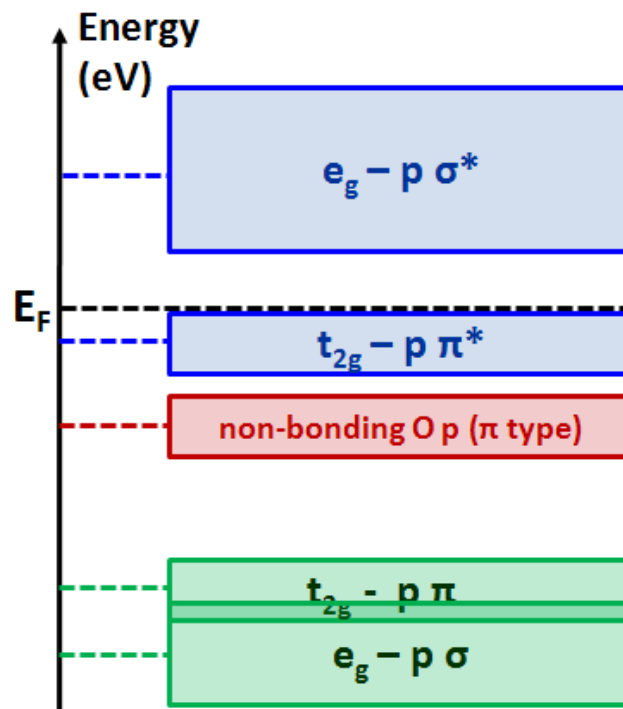
Fig. 41. Phase diagram of $\text{La}_{1-x}\text{Sr}_x\text{CoO}_3$ ($0 \leq x \leq 0.50$); adapted from [247]. Co(III) = low-spin; Co(II) = intermediate-spin; Co^{3+} = high-spin

- Fuchs et al., PRB 75, 144402 (2007)
- Rondinelli&Spaldin, PRB 79, 054409 (2009) NO
- Gupta&Mahadevan, PRB 79, 020406 (2009) YES

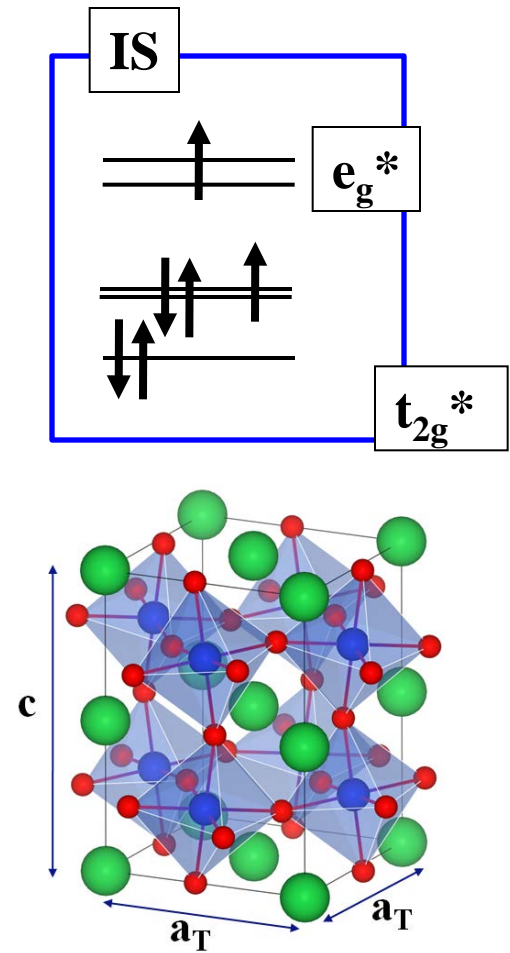
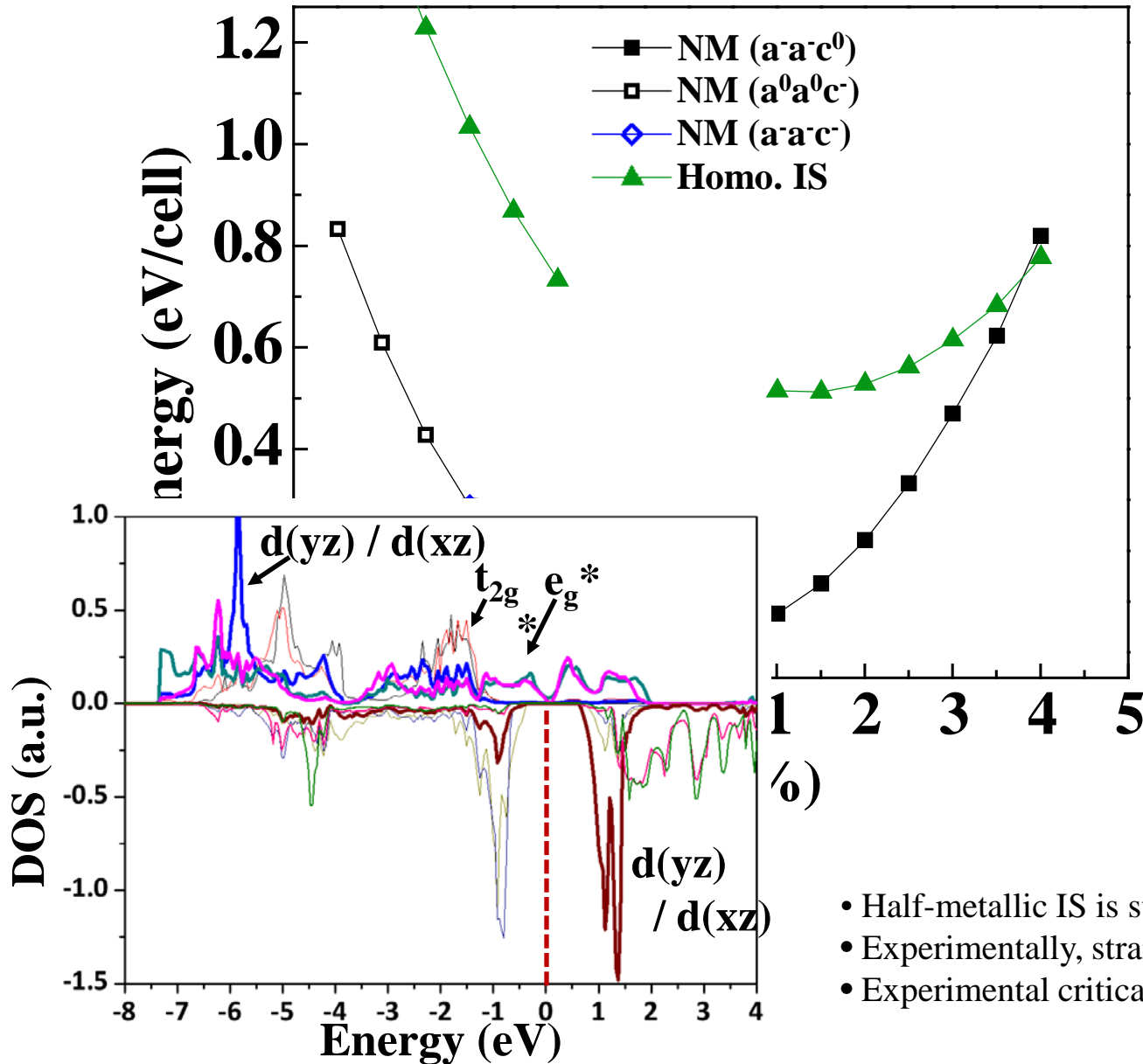
LaCoO₃



*Low spin (LS); $S = 0$



Energy vs. strain



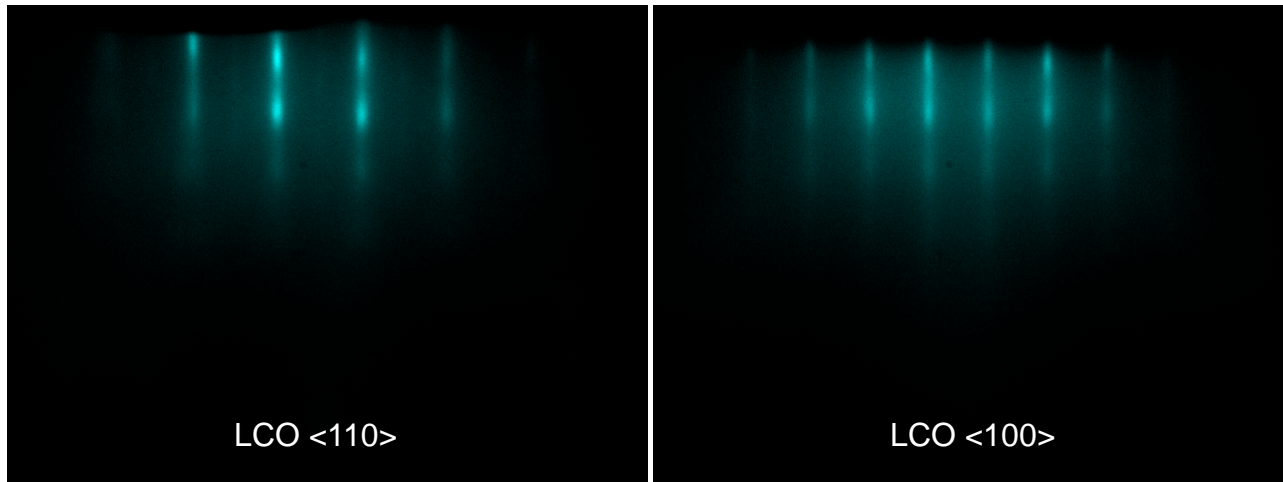
- Half-metallic IS is stabilized beyond 3.8%.
- Experimentally, strained LCO on STO is insulating.
- Experimental critical strain is less than 3.8%.

Issues related to MBE growth of LCO on Si

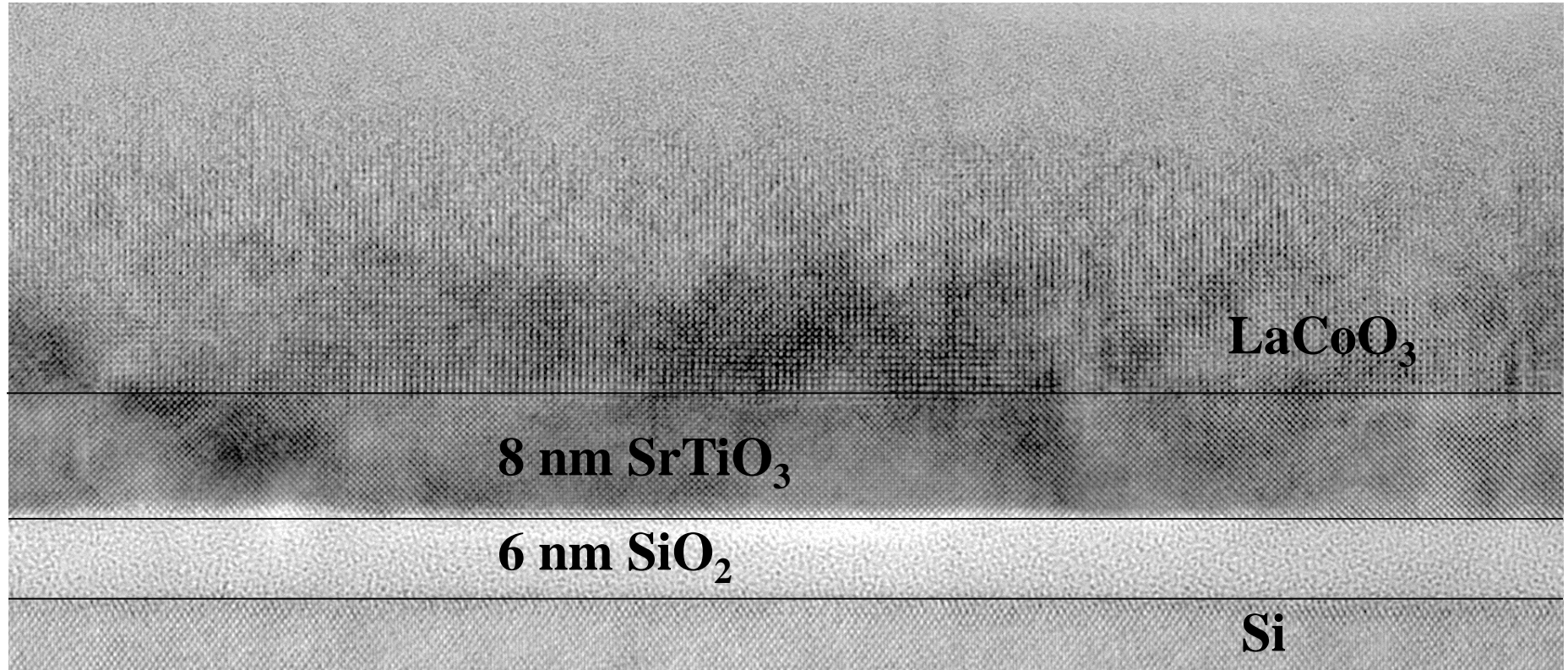
- Direct deposition of La, Co on Si in oxygen at high temperature will form CoSi_2 and SiO_2
 - Incommensurate or amorphous \rightarrow Prevents epitaxy
- Phase formation range of LaCoO_3 requires both high oxygen chemical potential and high temperature
 - Typical MBE growth conditions using molecular oxygen (10^{-6} torr) results in Co^{2+} oxidation state
- **To overcome these difficulties we will use an SrTiO_3/Si pseudo substrate**
 - Use an epitaxial template layer \rightarrow SrTiO_3 on Si
 - Use activated oxygen \rightarrow atomic oxygen from rf plasma source

Growth of LaCoO_3 on STO/silicon

- Atomic oxygen
 - 300 W rf power
 - 1×10^{-5} torr background oxygen pressure
- Substrate temperature 750°C
- Co-deposition of La and Co with matched fluxes
 - 2 unit cells per minute rate
- Slow cooling in oxygen
 - 10°C per minute to 100°C

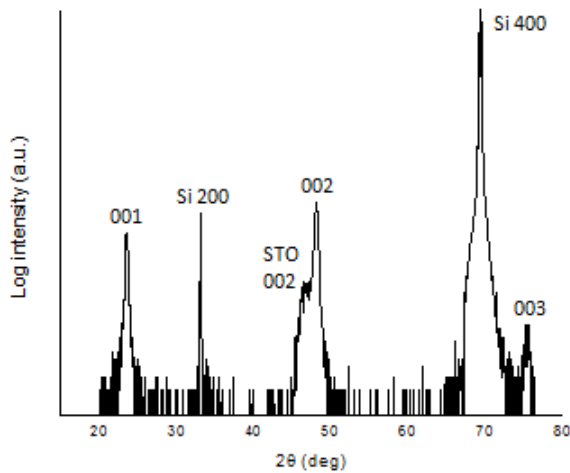


Cross-section TEM



X-ray diffraction

30 nm LCO/8 nm STO/Si



No secondary phases ($\text{La}_4\text{Co}_3\text{O}_{10}$, La_2CoO_4 , CoO)

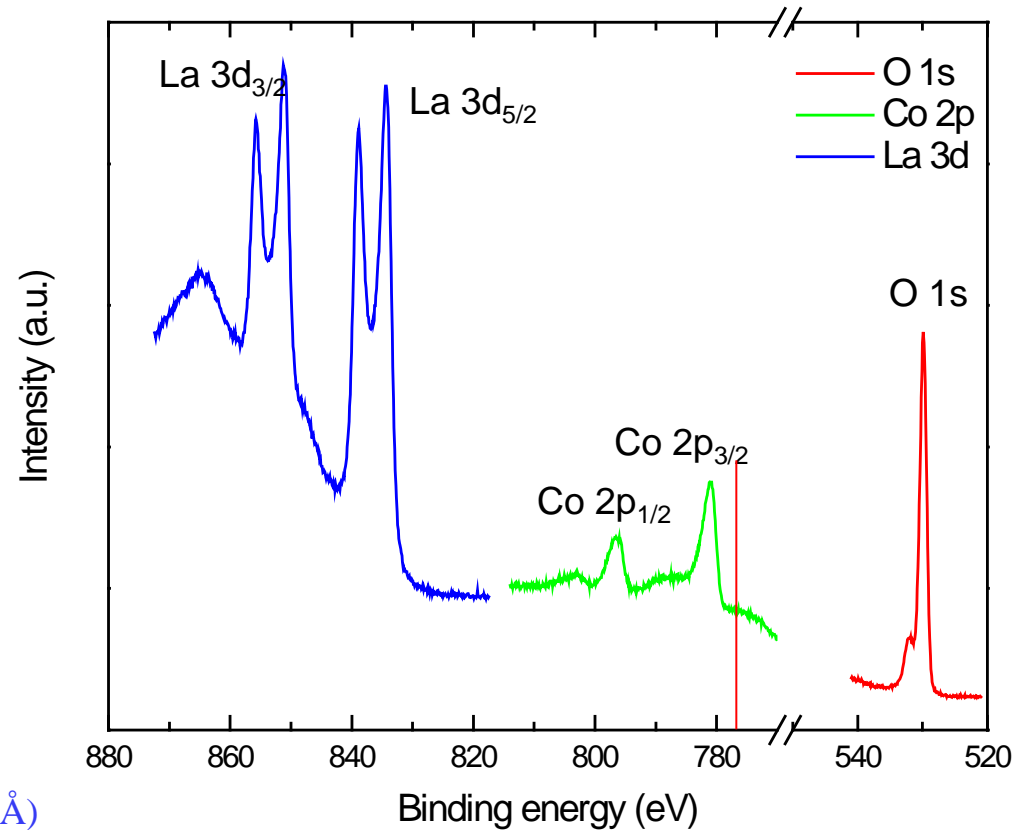
LaCoO_3 lattice parameters

(bulk $a = 3.80 \text{ \AA}$)

$c = 3.77 \text{ \AA}$

$a = 3.89 \text{ \AA}$ ← **Strained to SrTiO_3 ($a = 3.90 \text{ \AA}$)**

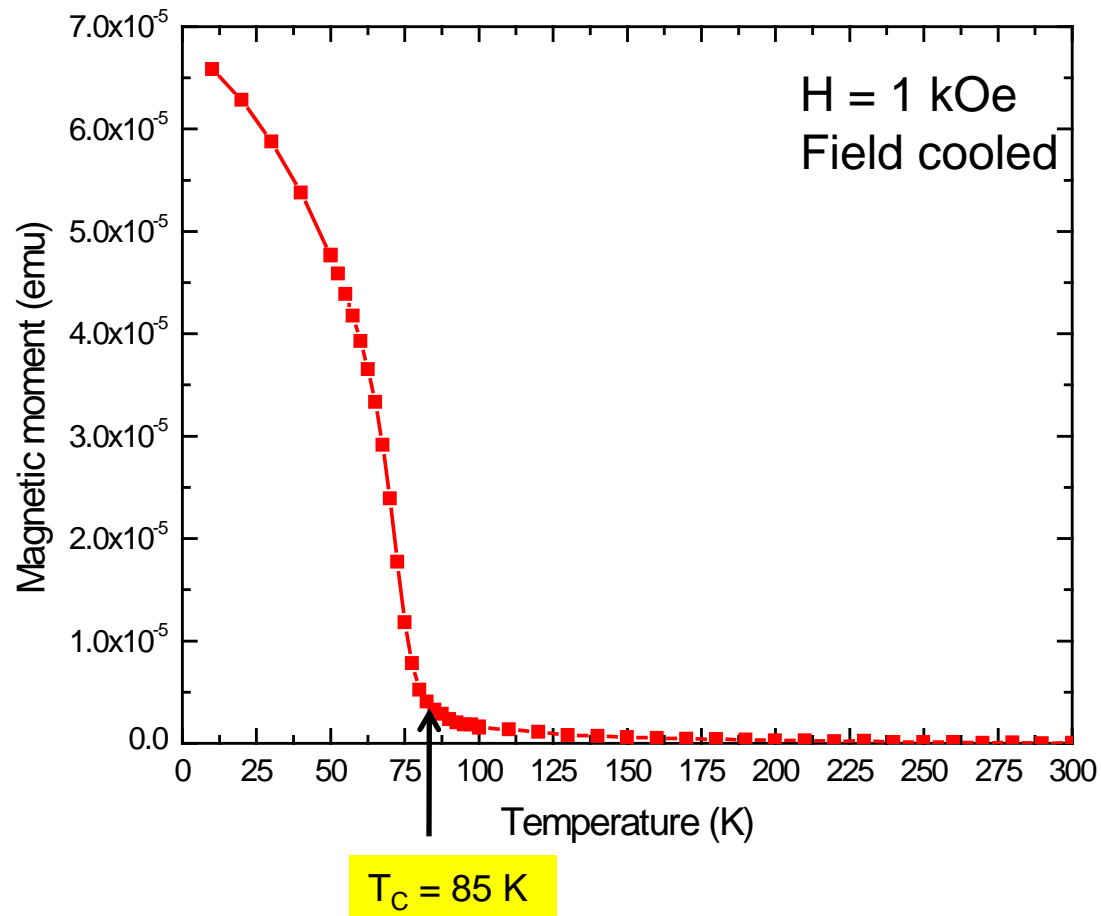
Core level spectra (XPS)



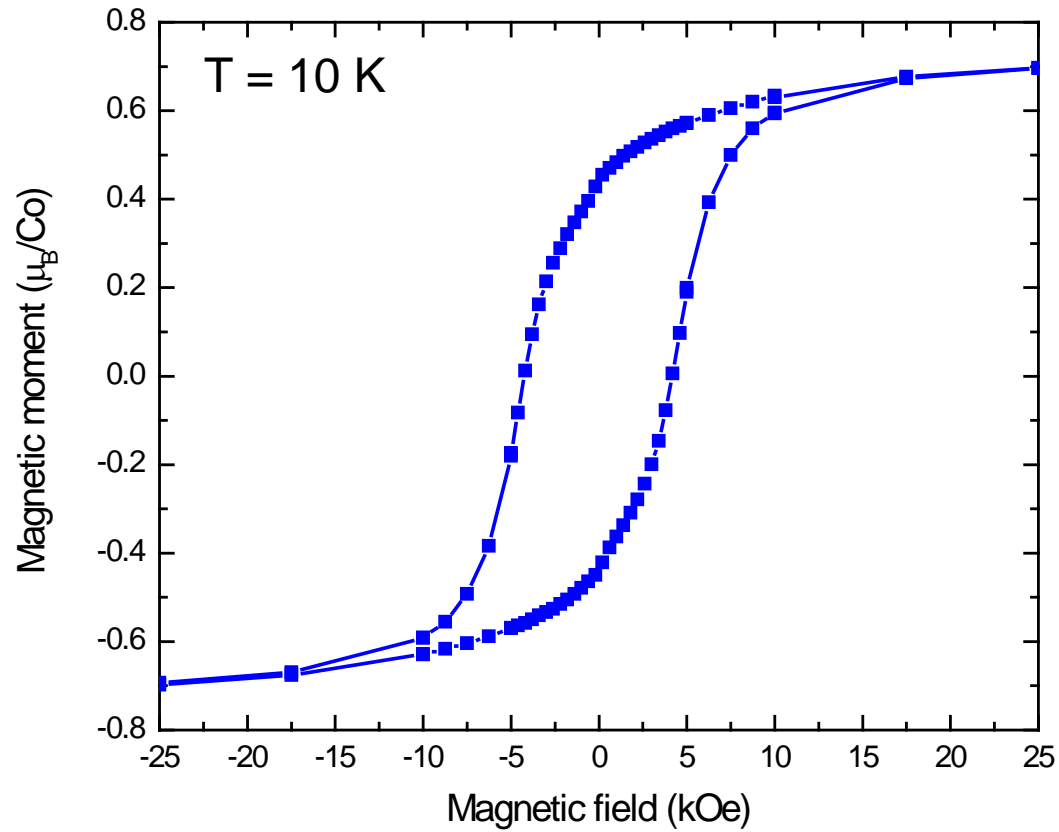
No Co metal detected in XPS

Spectra consistent with literature data for single crystal

Magnetization vs. temperature

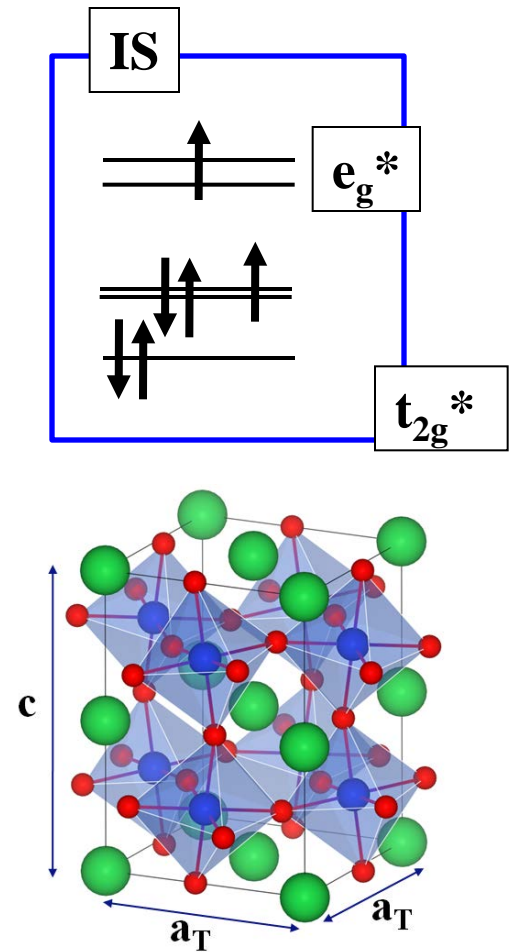
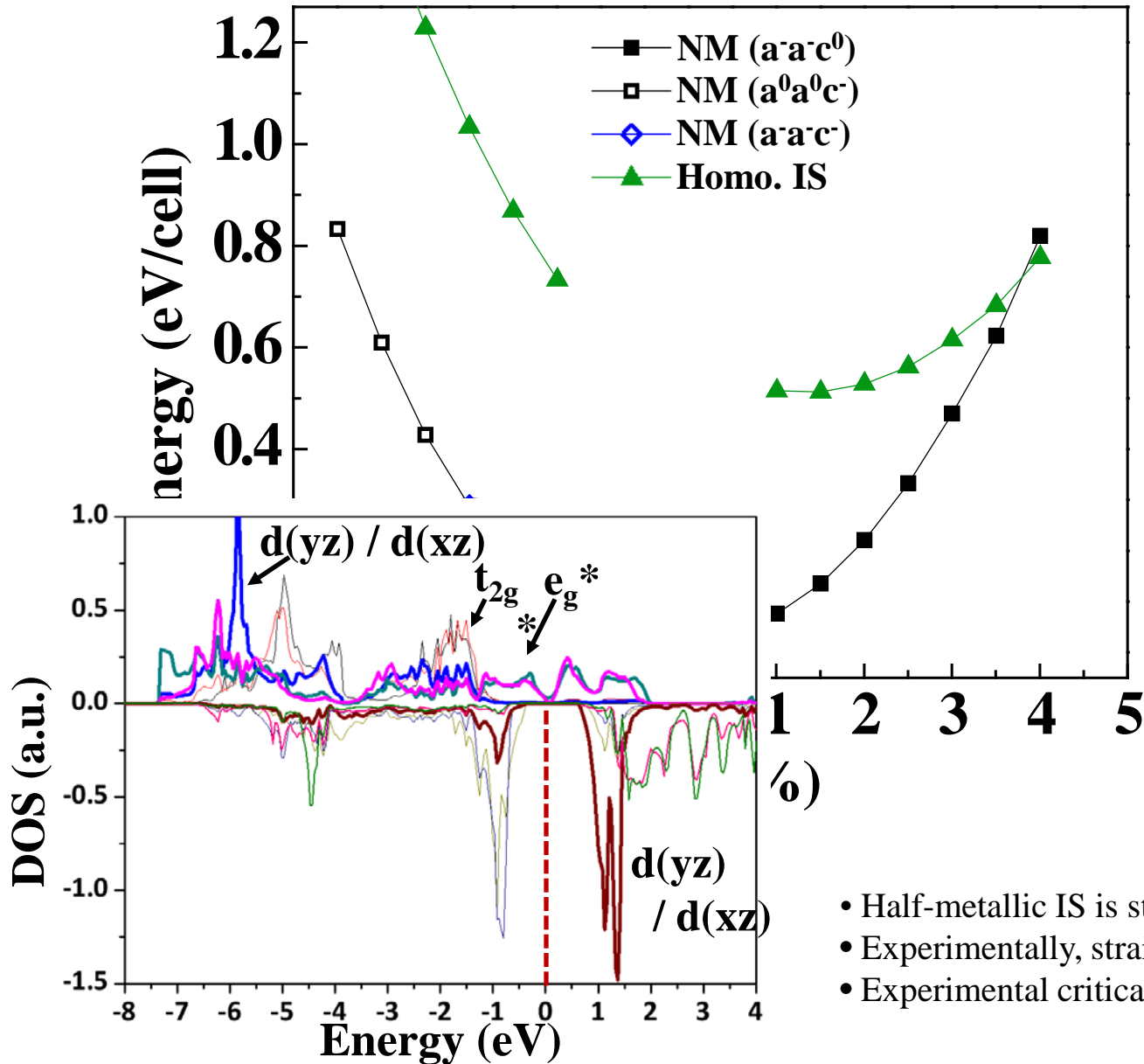


Magnetization vs. field



Posadas, et al., Appl. Phys. Lett. **98**, 053104, (2011).

Energy vs. strain

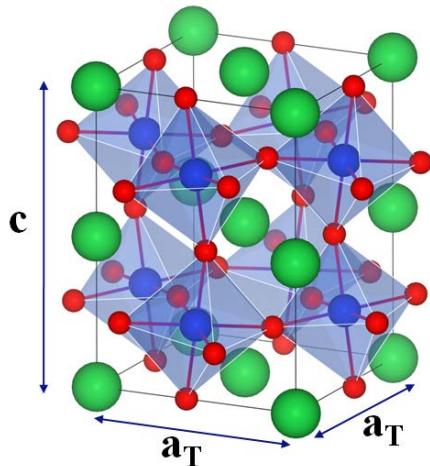


- Half-metallic IS is stabilized beyond 3.8%.
- Experimentally, strained LCO on STO is insulating.
- Experimental critical strain is less than 3.8%.

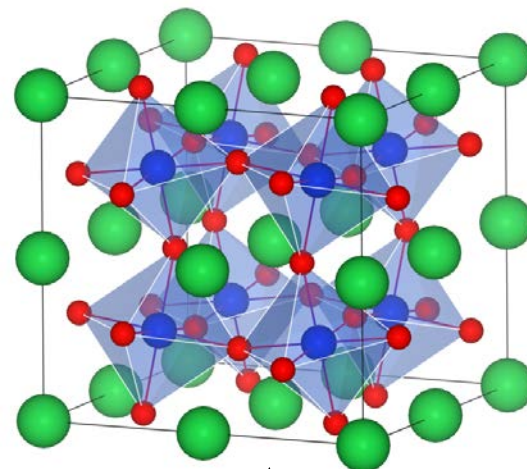
Supercells

$$\sqrt{2} \times \sqrt{2} \times 2$$

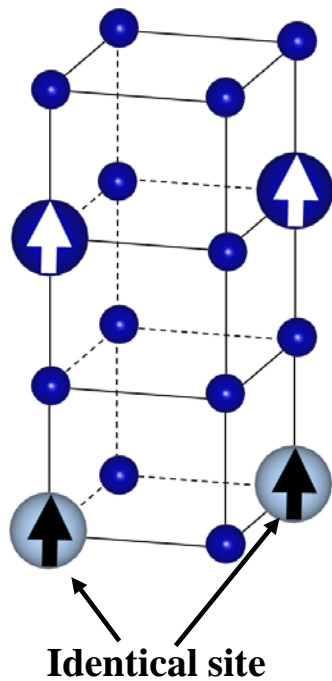
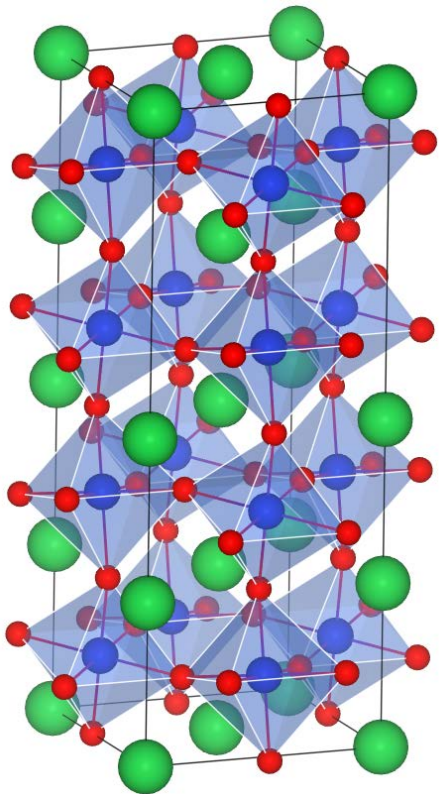
- 4 independent Co sites
2 in-plane, 2 out-of-plane



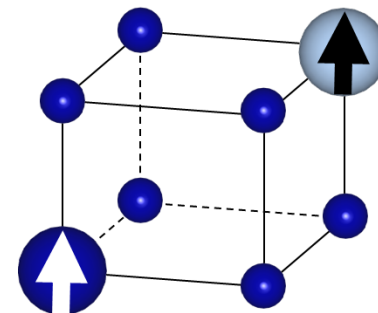
$$2 \times 2 \times 2$$



$$\sqrt{2} \times \sqrt{2} \times 4$$

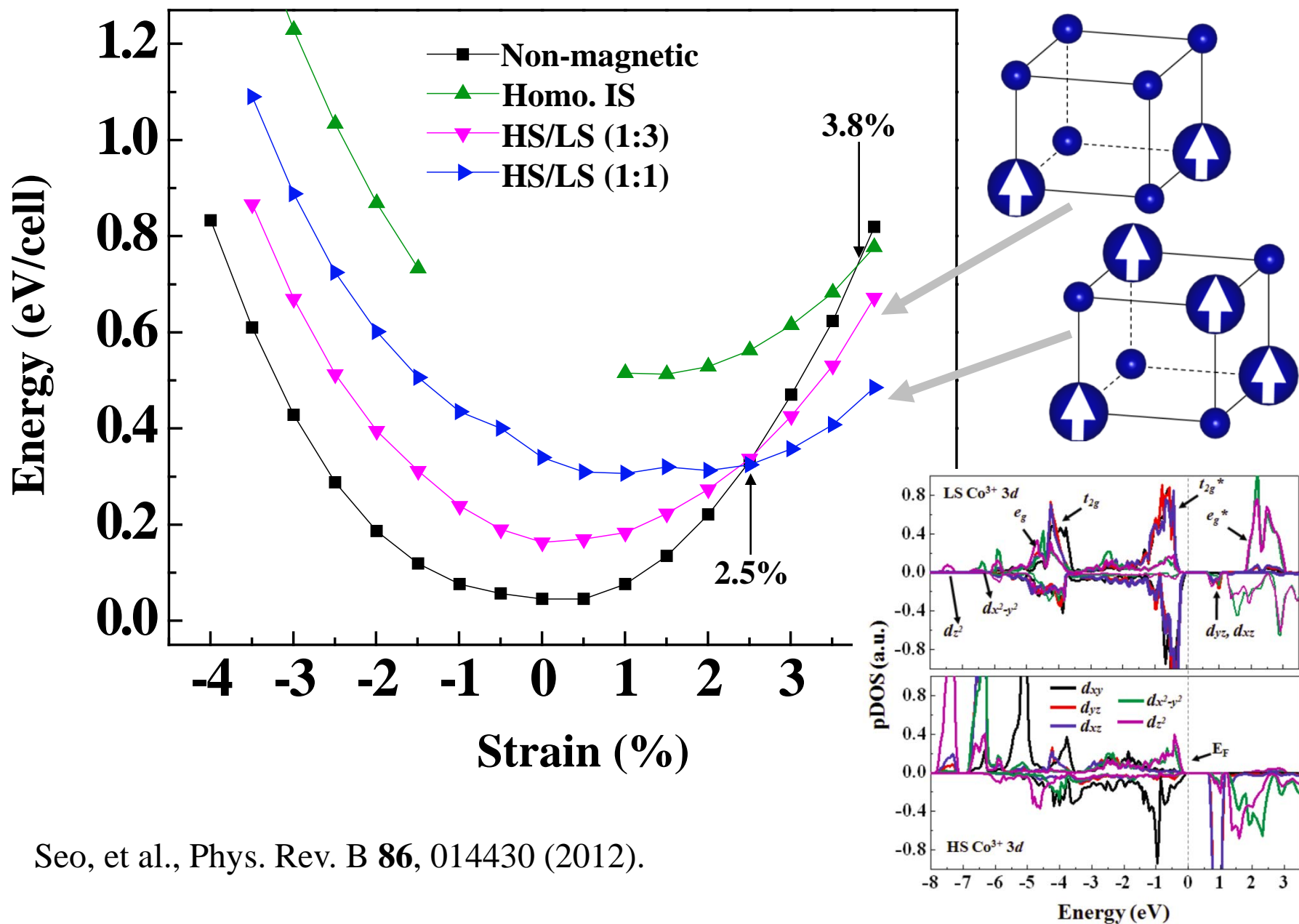


- 8 independent Co sites
2 in-plane, 4 out-of-plane



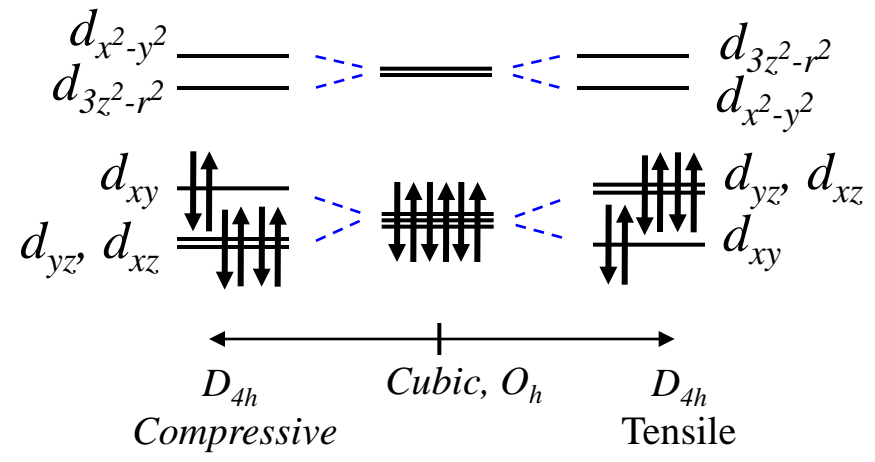
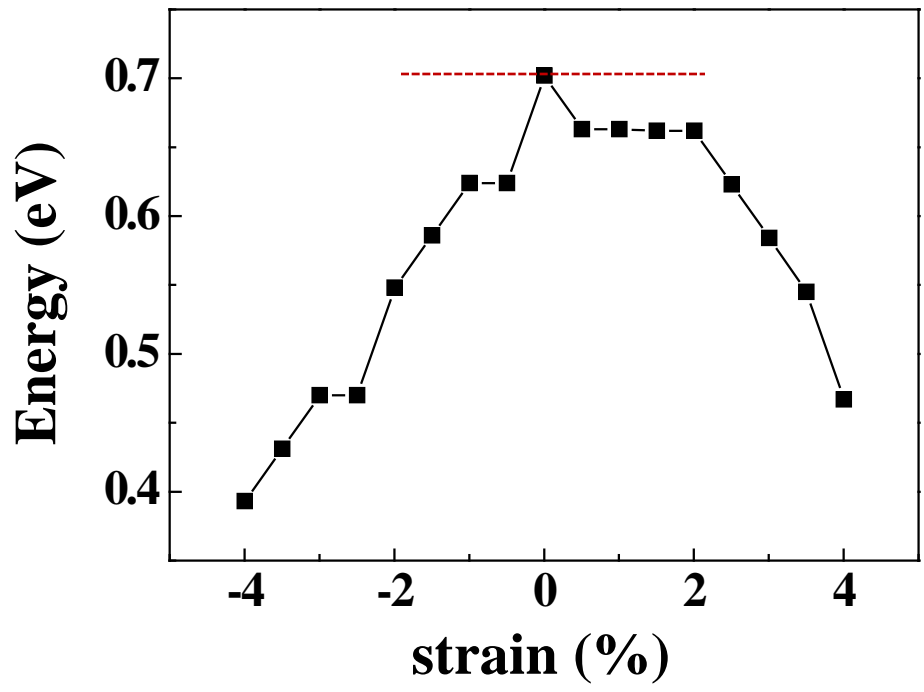
- 8 independent Co sites
4 in-plane, 2 out-of-plane

Energy vs. strain: HS/LS mixed states

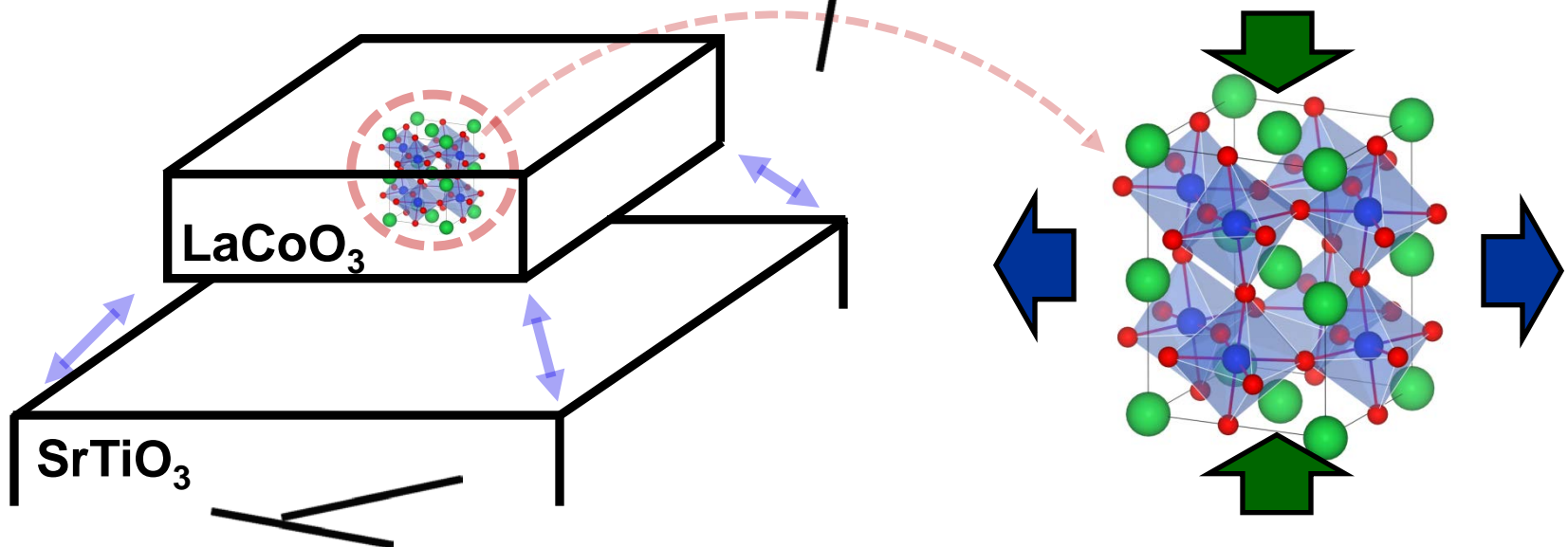


Seo, et al., Phys. Rev. B **86**, 014430 (2012).

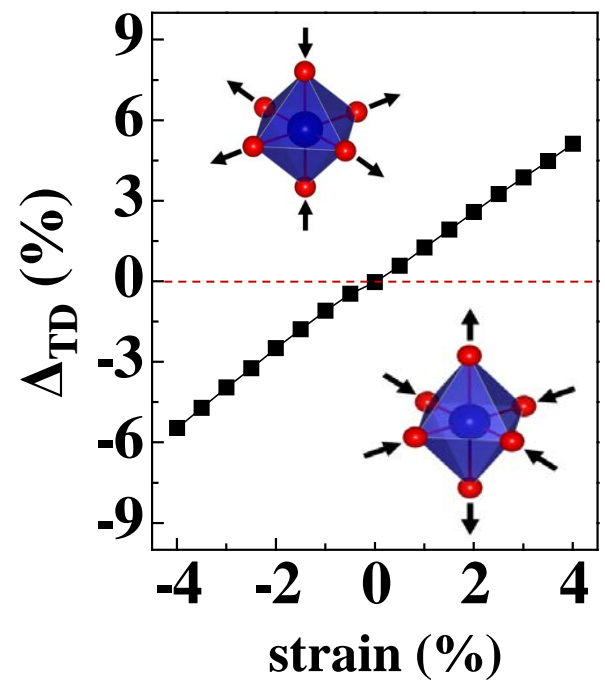
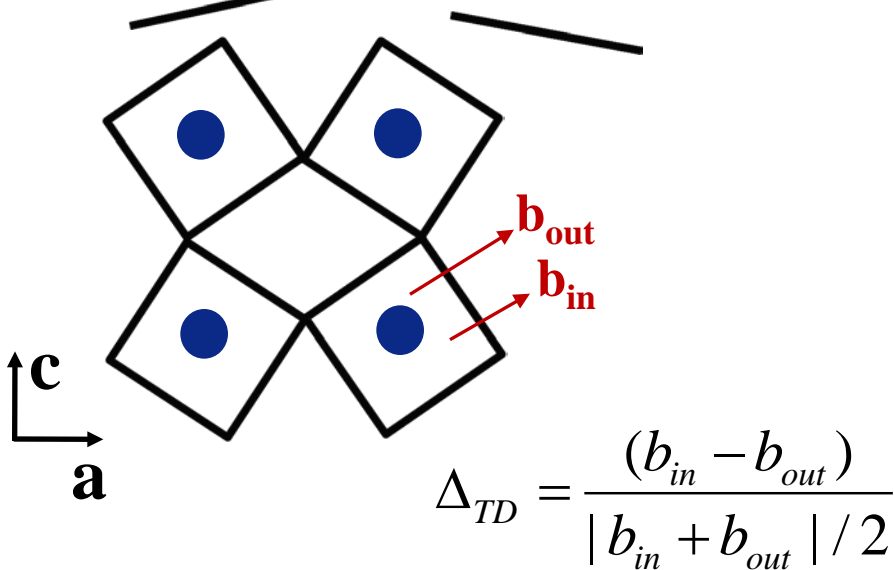
Band gap change as a function of strain



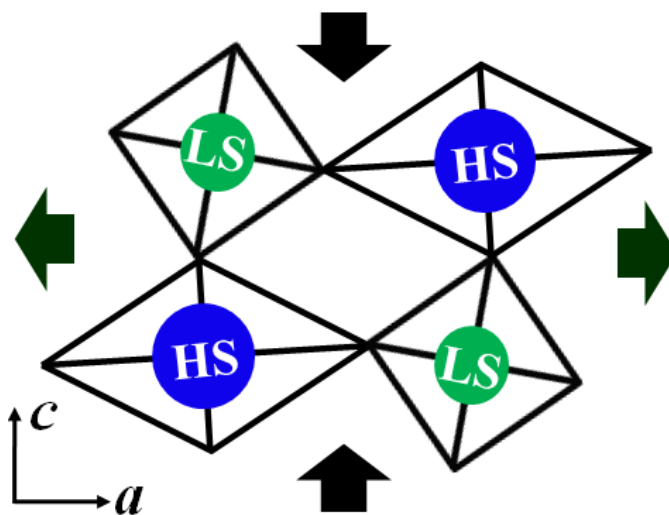
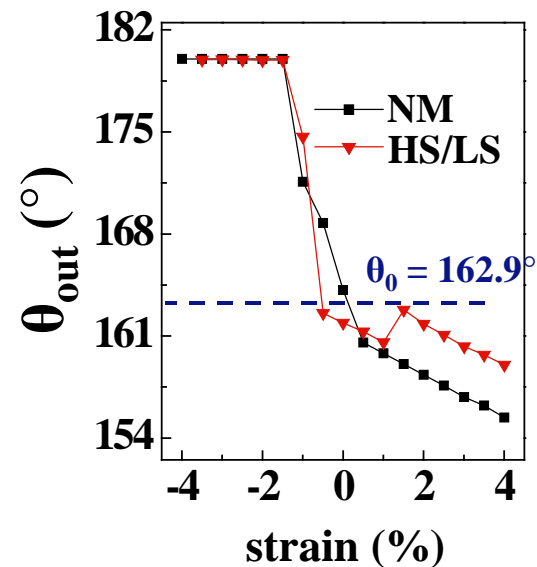
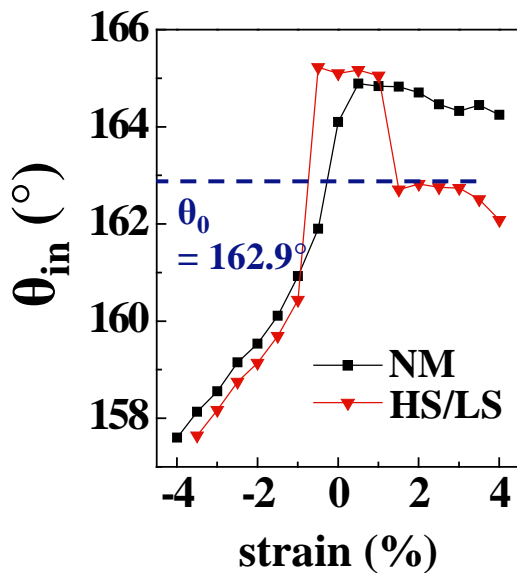
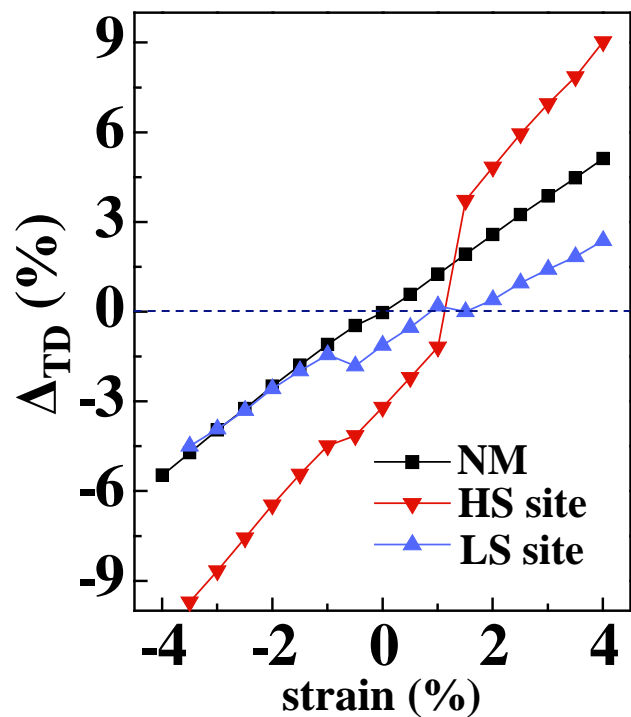
Strain accommodation



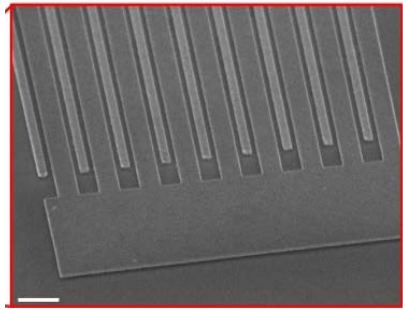
- Corner-sharing octahedral network with relatively rigid CoO_6 units under epitaxial stress



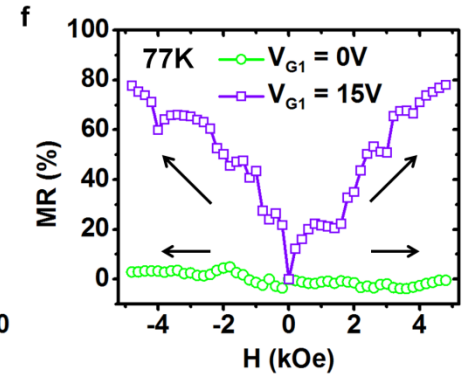
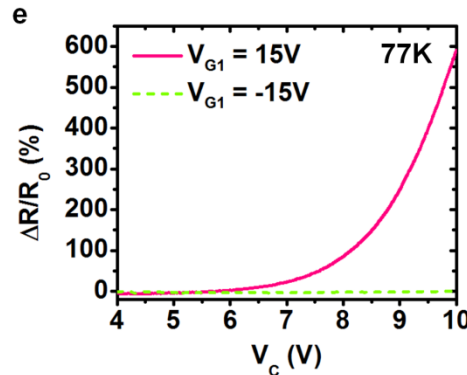
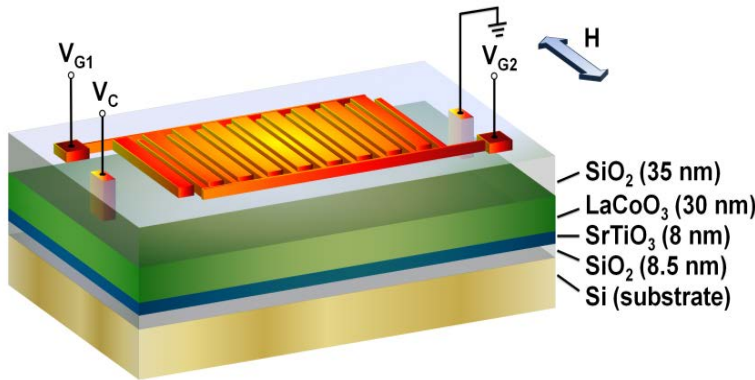
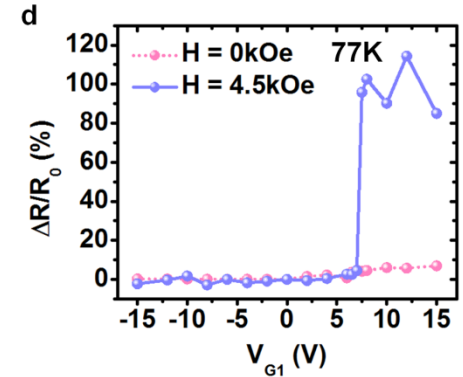
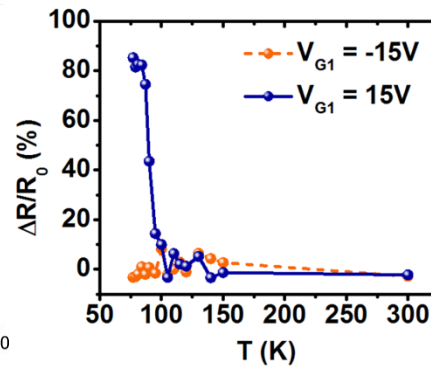
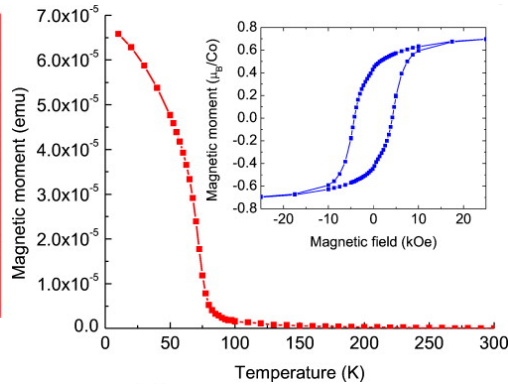
Bond lengths and angles



Voltage-switchable magnetoresistance in LaCoO_3



SEM image of device



Normally nonmagnetic LaCoO_3 becomes ferromagnetic below 85 K under tensile strain

No magnetoresistance above T_C for both voltage polarities

Magnetoresistance observed only below T_C and for only positive voltage

Critical voltage needed to observe magnetoresistance

Summary

- **First demonstration of epitaxial growth of magnetic LaCoO_3 on silicon.**
- **High quality crystalline LaCoO_3 layer epitaxially strained to underlying SrTiO_3 buffer (XRD, TEM, XPS), $T_C \sim 85$ K (SQUID)**
- **Beyond biaxial tensile strain of 2.5% local magnetic moments, originating from HS (S=2) states of Co^{3+} ions, emerge in the LS Co^{3+} matrix.**
- **The HS/LS state is insulating.**
- **The stabilization of the FM state is attributed to increased compliance of LCO when it has higher concentration of HS Co^{3+} ions. Despite the energy cost to excite LS Co^{3+} to HS state, LCO chooses this option and gains energy above tensile strain of 2.5% owing to the softness of the HS CoO_6 clusters.**
- **In contrast, compressive strain could not produce a magnetic state in LCO.**